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電子設計自動化演算法與實作  
Electronic Design Automation Algorithms and  
Implementation



**VLSI Testing  
NYCU**

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National Yang Ming Chiao Tung University  
Spring 2026**

# EDA Courses in DEE

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- **Undergraduate**
  - **Data structures**
  - **Discrete mathematics**
  - **Algorithms**
  - **Introduction to EDA**
- **Graduate**
  - **Advanced algorithms**
  - **Special topics in CAD**  
**(logic synthesis & verification) – front end**
  - **Physical design automation – back end**
  - **High level synthesis**
  - **Testing**

# Administrative Matters

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- **Time/Location:** Monday G and Thursday EF@ED116
- **Instructor:** Mango Chao
  - **E-mail:** [mango@nycu.edu.tw](mailto:mango@nycu.edu.tw)
  - **Office Hours:** Monday 11-11:50m (by appointment)
- **Teaching Assistants**
  - 潘信志 ([abcde123987654.ee10@nycu.edu.tw](mailto:abcde123987654.ee10@nycu.edu.tw))
  - 張皓儒 ([black1120rock@gmail.com](mailto:black1120rock@gmail.com))
  - 王堃誠 ([wan070708.c@nycu.edu.tw](mailto:wan070708.c@nycu.edu.tw))
  - 陳禹丞 ([perry910424@gmail.com](mailto:perry910424@gmail.com))
- **Prerequisites:** Data structures (or discrete math) & logic design
- **Text/Reference Books**
  - L.-T. Wang, Y.-W. Chang, and K.-T. Cheng, *Electronic Design Automation*, Morgan Kaufmann, 2009. ISBN: 978-0-12-374364-0
  - S. H. Gerez, *Algorithms for VLSI Design Automation*, John Wiley & Sons, 1999. ISBN: 0-471-98489-2.
  - G. De Micheli, *Synthesis and Optimization of Digital Circuits*, McGraw-Hill, Inc., 1994. ISBN: 0-07-01332-2.

# Grading Policy

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- **Grading Policy:**
  - Four programming assignments/labs: 40%
  - One exam (Late midterm: 40%)
  - Final project: 20% (with up to 10% bonus)
- **Assignments:**
  - Complete assignment by yourself (no credits for plagiarism)
  - No late assignment due (partial solutions may get partial credits)
- **Test (closed book):**
  - No discussions (no credits for plagiarism).
- **Class webpage:**
  - <https://tiger.iee.nycu.edu.tw/course/EDAIntro2026Spring/newe3>
- **Honor code:**
  - <https://tiger.iee.nycu.edu.tw/course/EDAIntro2026Spring/honorcode.pdf>
  - Download, sign, and submit your honor code on E3
  - Follow exam rules
  - Don't use AI to implement your code or report

# Final Project Information

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- Final project selection
  - Read an EDA paper from DAC/ICCAD/DATE in recent 3 years and write a report for it (>1000 words)
    - Get at most 15 points if only report is provided
    - Verify the paper by yourself can get extra 5~10 points
  - Attend CAD contest this year instead to get **higher** scores
    - Get 20 points if you submit your work
    - Get extra 5~10 points if your program passes the test (alpha test)
    - 1 people for one team
  - You should decide before the end of April, submit your decision to TA (register during May)

# Course Objectives

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- Study techniques for electronic design automation (EDA), a.k.a. computer-aided design (CAD)
- Study IC technology evolution and their impacts on the development of EDA tools
- **Study problem-solving (-finding) techniques!!!**

	f1	f2	f3	f4	f5
v1	x		x		x
v2	x	x	x		
v3			x	x	x
v4	x	x			x

# Course Contents

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- Introduction to VLSI design flow/styles/automation, EDA business(5 hrs) + EDA algorithm review (1 hr)
- **Physical design**: partitioning, floorplanning, placement, and routing (21 hrs)
- **Logic synthesis** and verification (9 hrs)
- Timing analysis (3 hrs)
- **Testing** (6 hrs)
- Introduction to ML/DL EDA (1 hr)
- Simulation (3 hrs)

**DEE3502**

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# **Introduction to Electronic Design Automation**

江蕙如

**Hui-Ru Jiang**

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*<http://eda.ee.nctu.edu.tw/hrjiang>*

**Department of Electronics Engineering**

**National Chiao Tung University**

**Hsinchu 300, Taiwan**

**Spring 2007**

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# Introduction to Computer-Aided Design of VLSI Circuits

台灣大學電機系 張耀文

清華大學電機系 黃錫瑜

交通大學資科系 李毅郎

中央大學電機系 劉建男

元智大學資工系 林榮彬

教育部

超大型積體電路與系統設計教育改進計畫

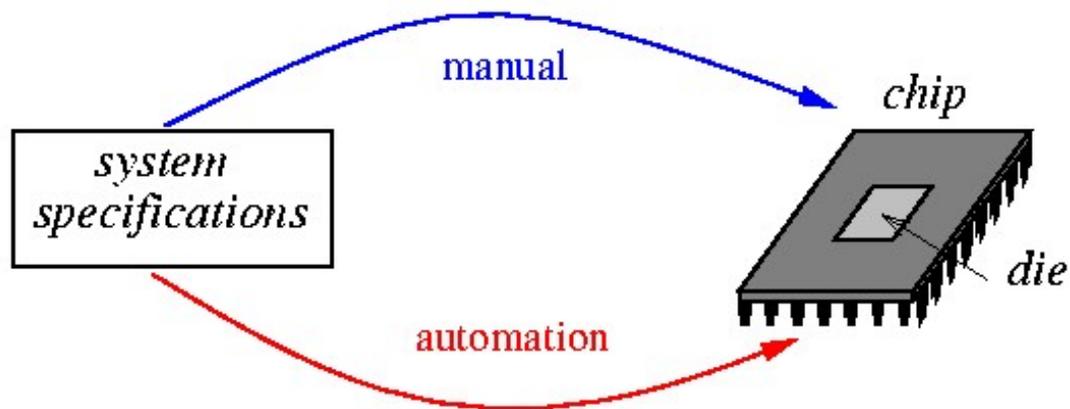
EDA聯盟



# Unit 1: Introduction

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- Course contents:
  - Introduction to VLSI design flow/methodologies/styles
  - Introduction to VLSI design automation tools
  - The business of EDA
  - Semiconductor technology roadmap and future trends



# Evolving CAD / EDA

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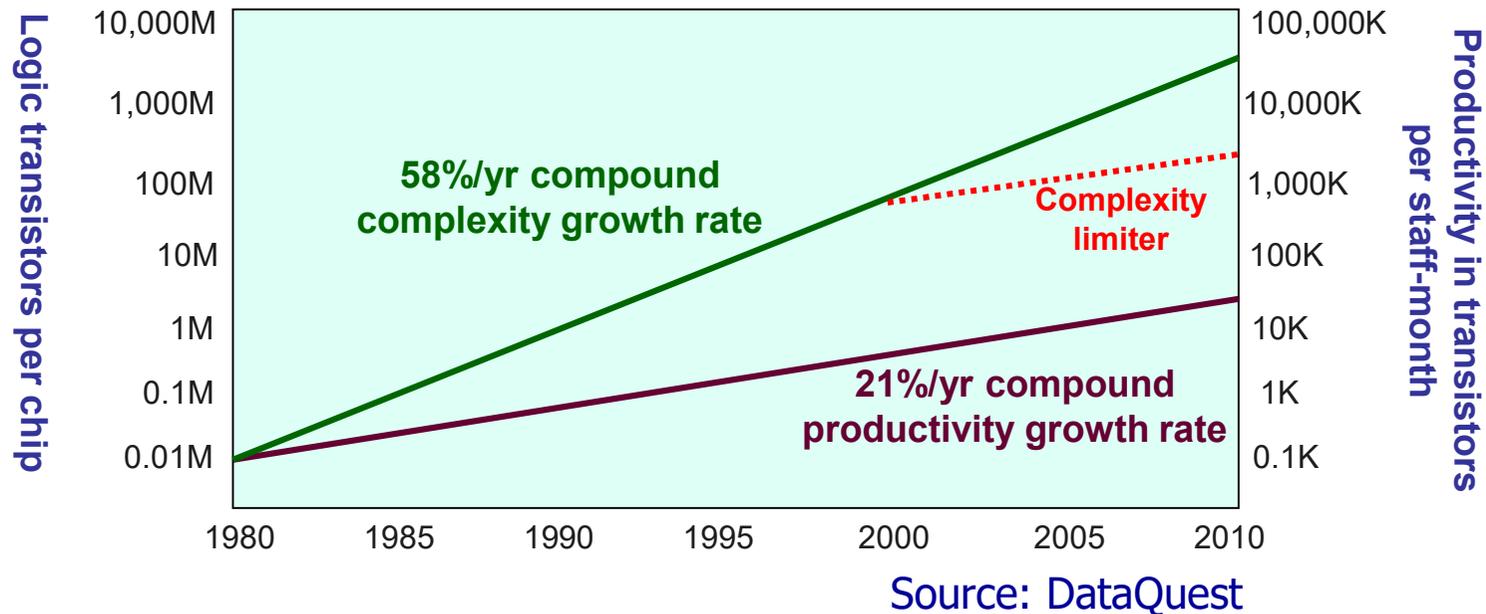
- The Industrial Revolution
  - Application of power-driven machinery to manufacturing (1750—1830)
- The 2nd Industrial Revolution!
  - Application of electronic devices to information processing (1950—present)
- Electronic systems evolve in a fascinating speed
  - Design challenges emerge and shift in this evolution
  - CAD tools exist and evolve along with the design challenges

# Mission of CAD / EDA

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- CAD tools aim at **automating** VLSI design process and optimizing **all** design instances (not just a specific design)

# Mission of CAD / EDA: Solving Productivity Crisis



- Human factors may limit design more than technology.
- Keys to solve the productivity crisis: **CAD (tool & methodology)**, hierarchical design, abstraction, IP reuse, platform-based design, etc.

# Discipline of CAD / EDA

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- EDA is a field with rich applications from theoretical computer science, operations research, mathematics as well as physics
  - Algorithms, complexity theory
  - Automata theory, logics, games
  - Probability, statistics
  - Algebra
  - Numerical analysis, matrix computation
  - Device physics
  - ...
- EDA is also a paradise for software engineers
  - Modern SAT solvers (e.g., GRASP, Chaff, BerkMin, MiniSAT) are developed greatly due to EDA

# Brief History of EDA

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- The first generation
  - 1960's: circuit board physical design automation
  - 1970's: simulation, device modeling
    - SPICE (analog simulator)
    - Technology CAD
    - Layout verification and editor
- The second generation
  - 1980's
    - LSI physical design (APR), two-level logic minimization, testing
    - Logic simulator
- The third generation
  - 1990's
    - Multi-level and sequential optimization
    - RTL methodology/synthesis and simulators, verification
- After 2000: system-level synthesis, design for manufacturing, software verification

# Analogy for Electronic System Design

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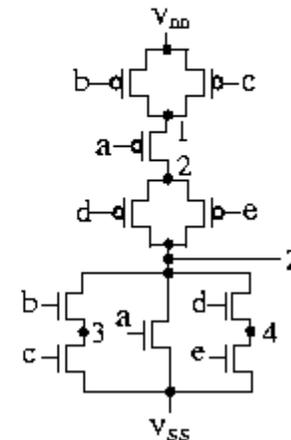
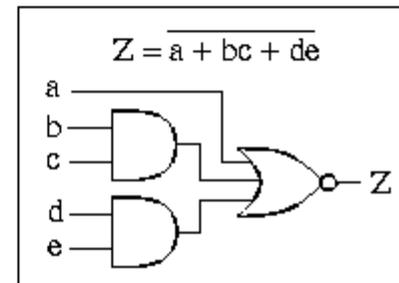
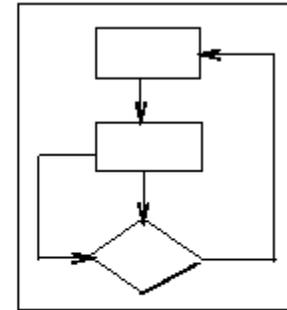
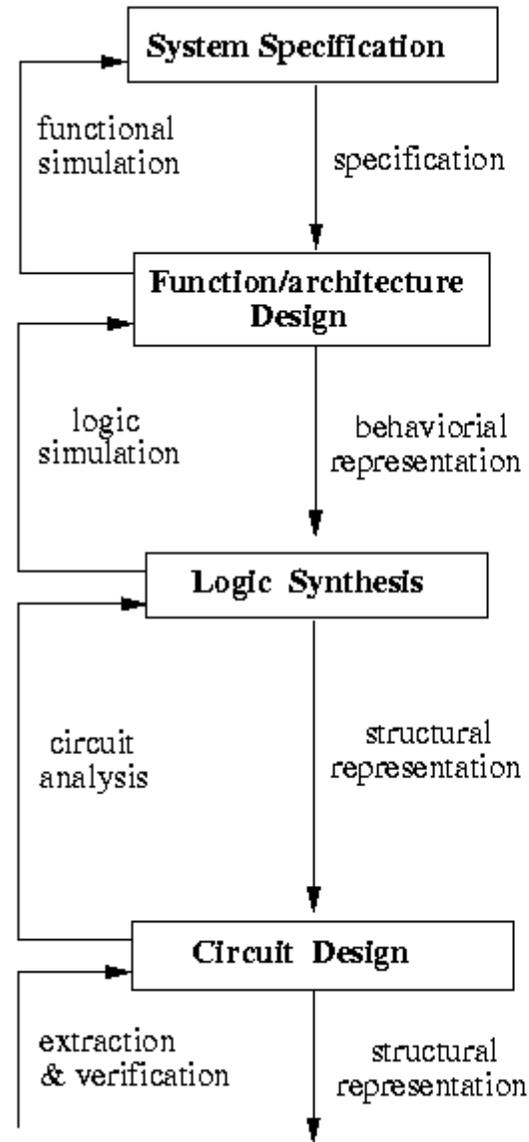
- City design
  - City planners, city architects, civil engineers and city council
- System design
  - System architects, design engineers, layout designers and software engineers/programmers
- For example, **system architects** decide which portions of the system will be implemented in hardware (islands and buildings), and which will be implemented in software (books of instructions in the library)

# Traditional VLSI Design Cycles

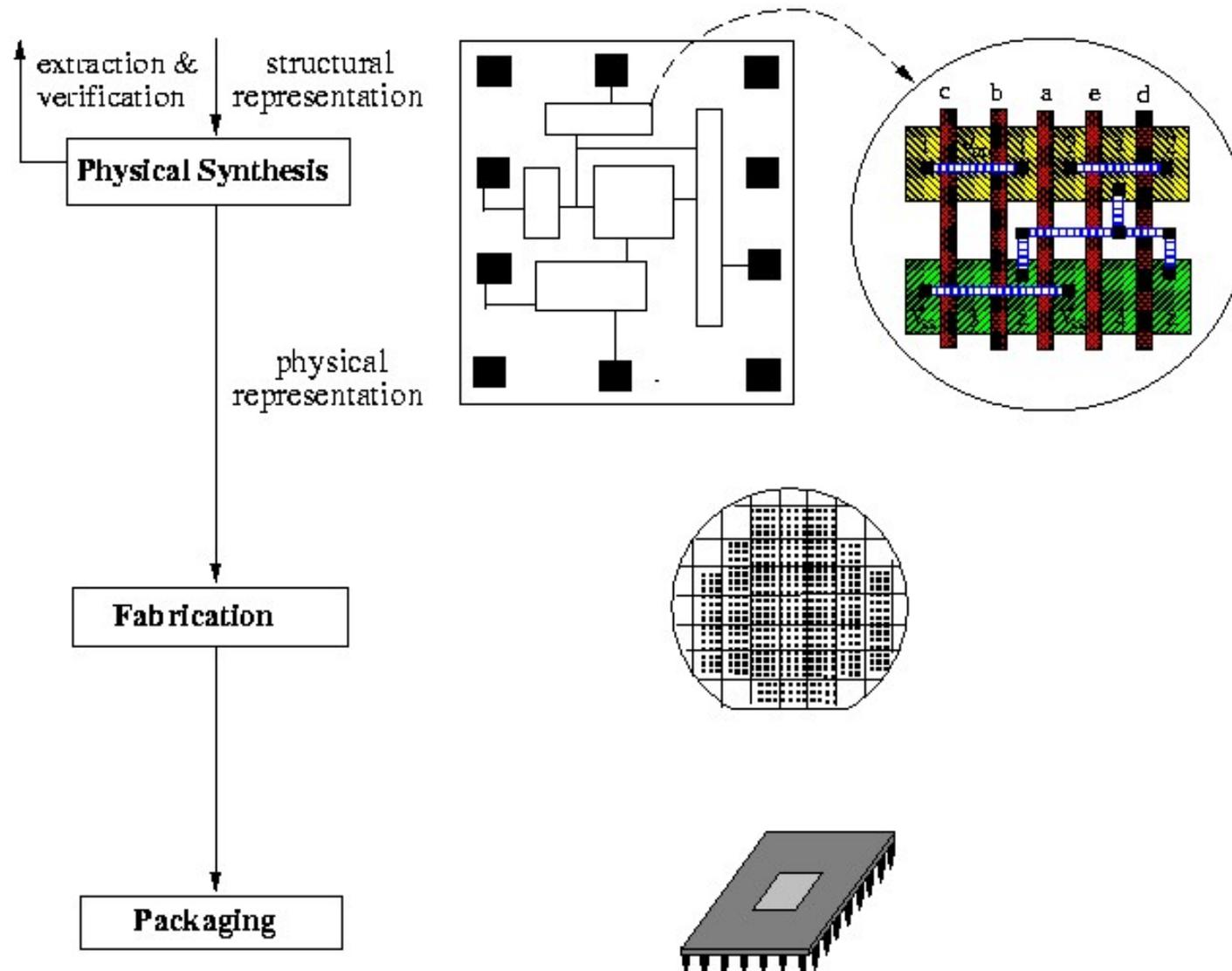
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1. System specification
2. Functional design
3. Logic synthesis
4. Circuit design
5. Physical design and verification
6. Fabrication
7. Packaging
  - Other tasks involved: testing, simulation, etc.
  - Design metrics: area, speed, power dissipation, noise, design time, testability, etc.
  - Design revolution: interconnect (not gate) delay dominates circuit performance in deep submicron era.
    - Interconnects are determined in physical design.
    - Shall consider interconnections in early design stages.

# Traditional VLSI Design Flow



# Traditional VLSI Design Flow (Cont'd)



# Design Actions

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- **Synthesis:** increasing information about the design by providing more detail (e.g., logic synthesis, physical synthesis).
- **Analysis:** collecting information on the quality of the design (e.g., timing analysis).
- **Verification:** checking whether a synthesis step has left the specification intact (e.g., layout verification).
- **Optimization:** increasing the quality of the design by rearrangements in a given description (e.g., logic optimizer, timing optimizer).
- **Design Management:** storage of design data, cooperation between tools, design flow, etc. (e.g., database).

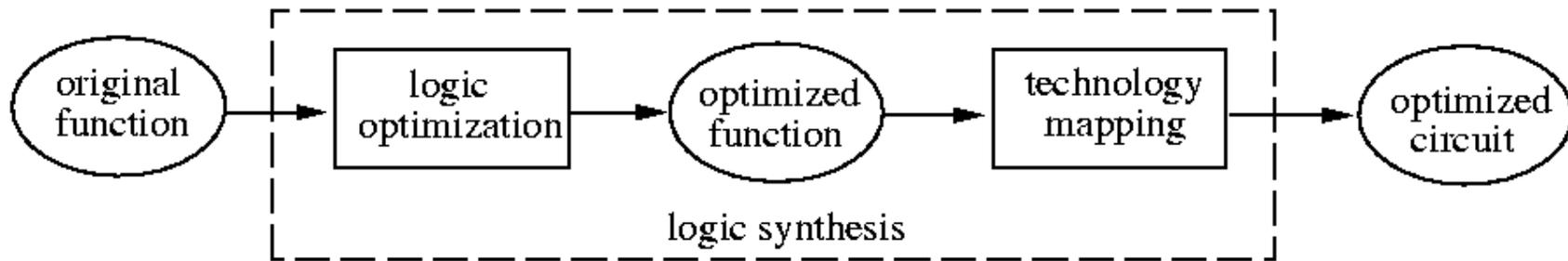
# Design Issues and Tools

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- System-level design
  - Partitioning into hardware and software, co-design, co-simulation, etc.
  - Cost estimation, design-space exploration
- Algorithmic-level design
  - Behavioral descriptions
  - High-level simulation
- From algorithms to hardware modules
  - High-level (or architectural) synthesis
- Logic design
  - Schematic entry
  - Register-transfer level and logic synthesis
  - Gate-level simulation (functionality, power, etc)
  - Timing analysis
  - Formal verification

# Logic Design/Synthesis

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- **Logic synthesis** programs transform Boolean expressions into logic gate networks in a particular library
- Optimization goals: minimize area, delay, power, etc
- **Technology-independent** optimization: logic optimization
  - Optimizes Boolean expression equivalent.
- **Technology-dependent** optimization: **technology mapping/library binding**
  - Maps Boolean expressions into a particular cell library.

# Logic Optimization Examples

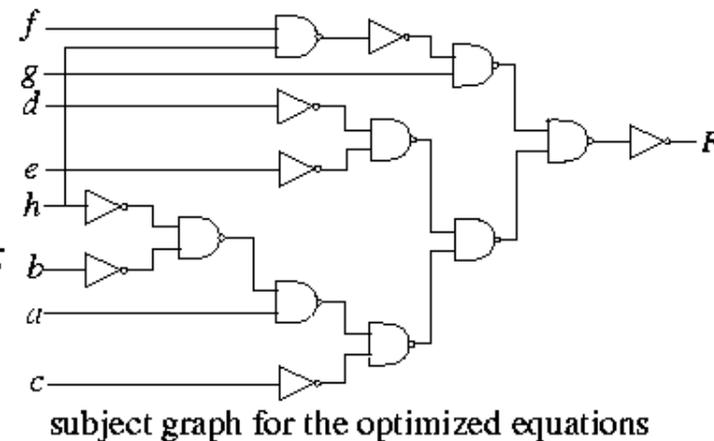
- **Two-level:** minimize the # of product terms.

–  $F = \bar{x}_1\bar{x}_2\bar{x}_3 + \bar{x}_1\bar{x}_2x_3 + x_1\bar{x}_2\bar{x}_3 + x_1\bar{x}_2x_3 + x_1x_2\bar{x}_3 \Rightarrow F = \bar{x}_2 + x_1\bar{x}_3.$

- **Multi-level:** minimize the #'s of literals, variables.

– E.g., equations are optimized using a smaller number of literals.

$t1 = a + b c;$	logic optimization →	$t1 = d + e;$
$t2 = d + e;$		$t2 = b + h;$
$t3 = a b + d;$		$t3 = a t2 + c;$
$t4 = t1 t2 + f g;$		$t4 = t1 t3 + f g h;$
$t5 = t4 h + t2 t3;$		
$F = t5';$		



- Methods/CAD tools: Quine-McCluskey method (exponential-time exact algorithm), Espresso (heuristics for two-level logic), MIS (heuristics for multi-level logic), Synopsys, etc.

# Design Issues and Tools (cont'd)

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- Transistor-level design
  - Switch-level simulation
  - Circuit simulation
- Physical (layout) design
  - Partitioning
  - Floorplanning and Placement
  - Routing
  - Layout editing and compaction
  - Design-rule checking
  - Layout extraction
- Design management
  - Data bases, frameworks, etc.
- **Silicon compilation:** *from algorithm to mask patterns*
  - The *idea* is approached more and more, but still far away from a single *push-button* operation

# Circuit Simulation of a CMOS Inverter (0.6 $\mu\text{m}$ )

```
M1 3 2 0 0 nch W=1.2u L=0.6u AS=2.16p PS=4.8u AD=2.16p PD=4.8u
M2 3 2 1 1 pch W=1.8u L=0.6u AS=3.24p PS=5.4u AD=3.24p PD=5.4u
CL 3 0 0.2pF
```

```
VDD 1 0 3.3
```

```
VIN 2 0 DC 0 PULSE (0 3.3 0ns 100ps 100ps 2.4ns 5ns)
```

```
.LIB '../mod_06' typical
```

```
.OPTION NOMOD POST INGOLD=2 NUMDGT=6 BRIEF
```

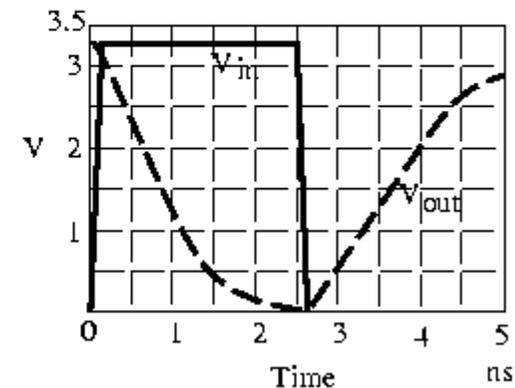
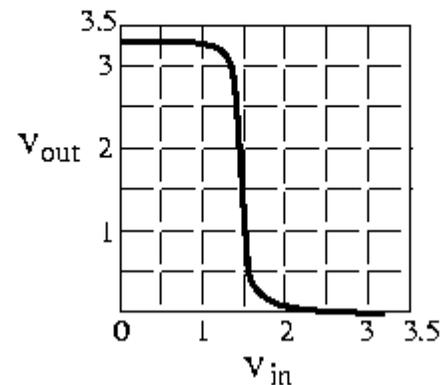
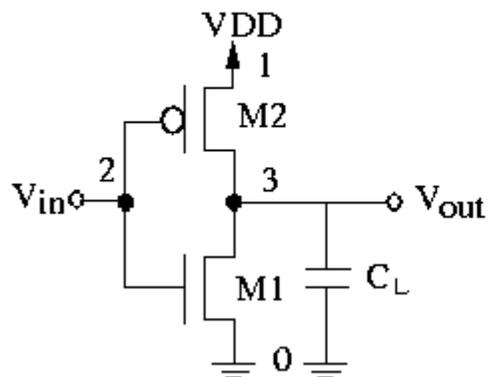
```
.DC VIN 0V 3.3V 0.001V
```

```
.PRINT DC V(3)
```

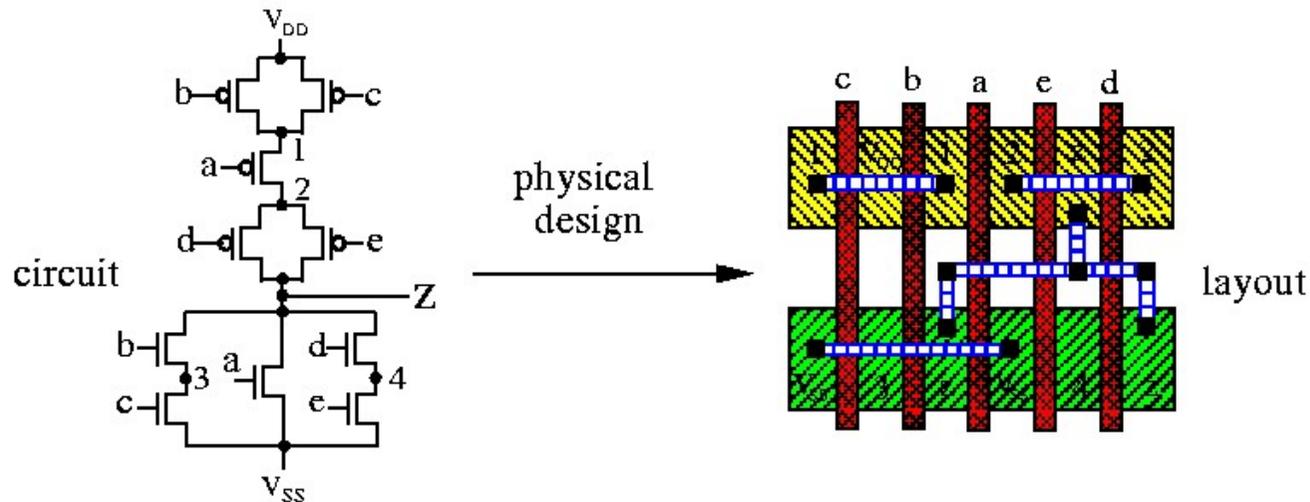
```
.TRAN 0.001N 5N
```

```
.PRINT TRAN V(2) V(3)
```

```
.END
```

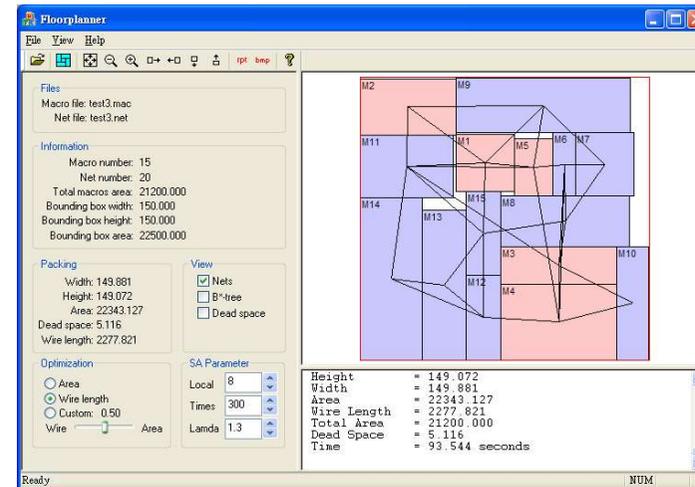
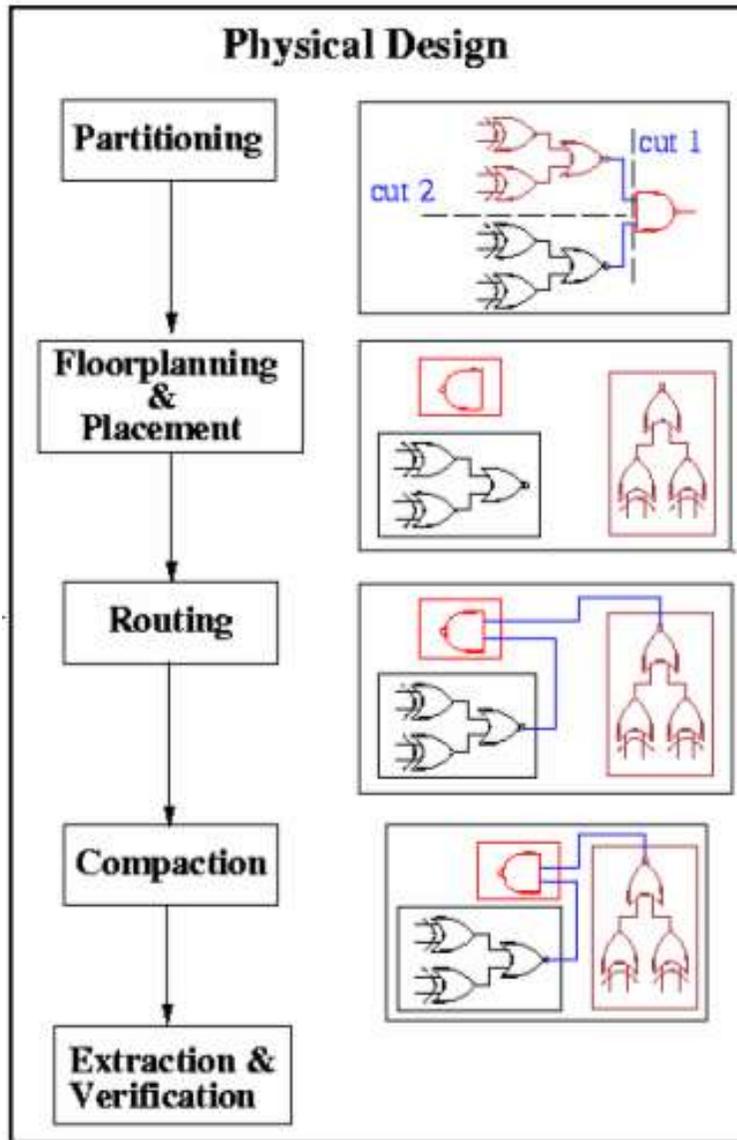


# Physical Design



- Physical design converts a circuit description into a geometric description.
- The description is used to manufacture a chip.
- Physical design cycle:
  1. Logic partitioning
  2. Floorplanning and placement
  3. Routing
  4. Compaction
- Others: circuit extraction, timing verification and design rule checking

# Physical Design Flow



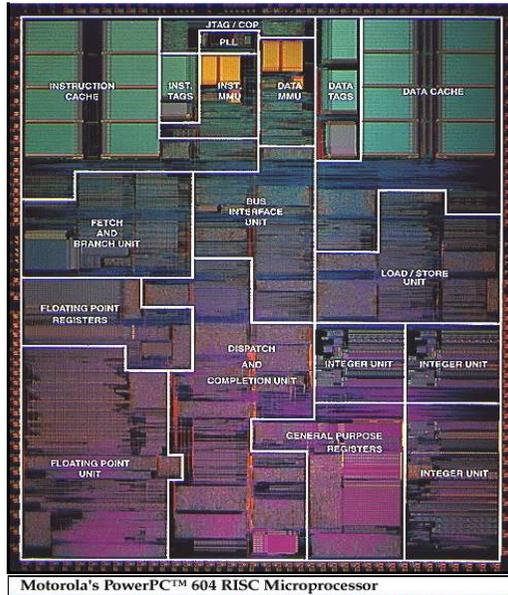
**B\*-tree based floorplanning system**



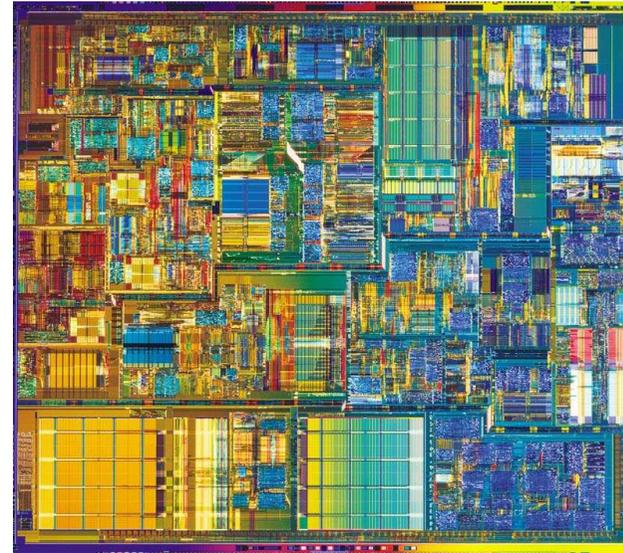
**A routing system**

# Floorplan Examples

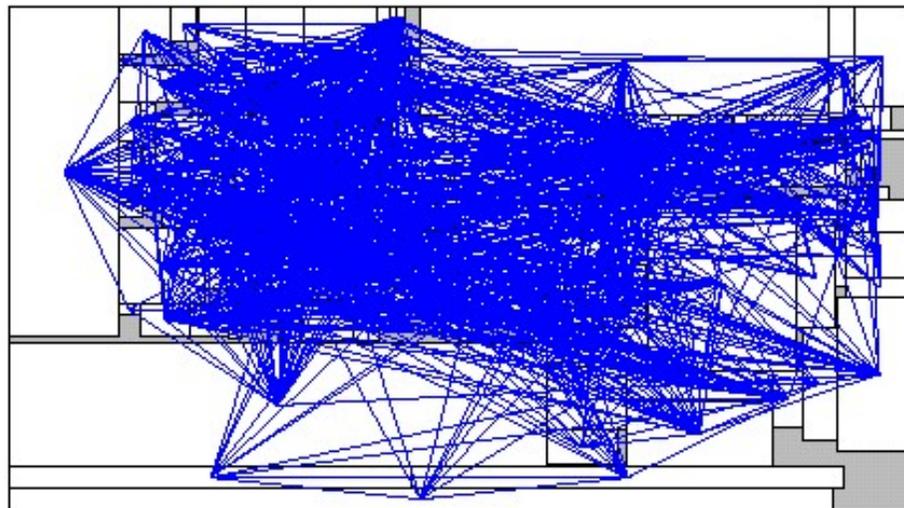
PowerPC  
604



Intel  
Pentium 4



A floorplan  
with  
interconnections

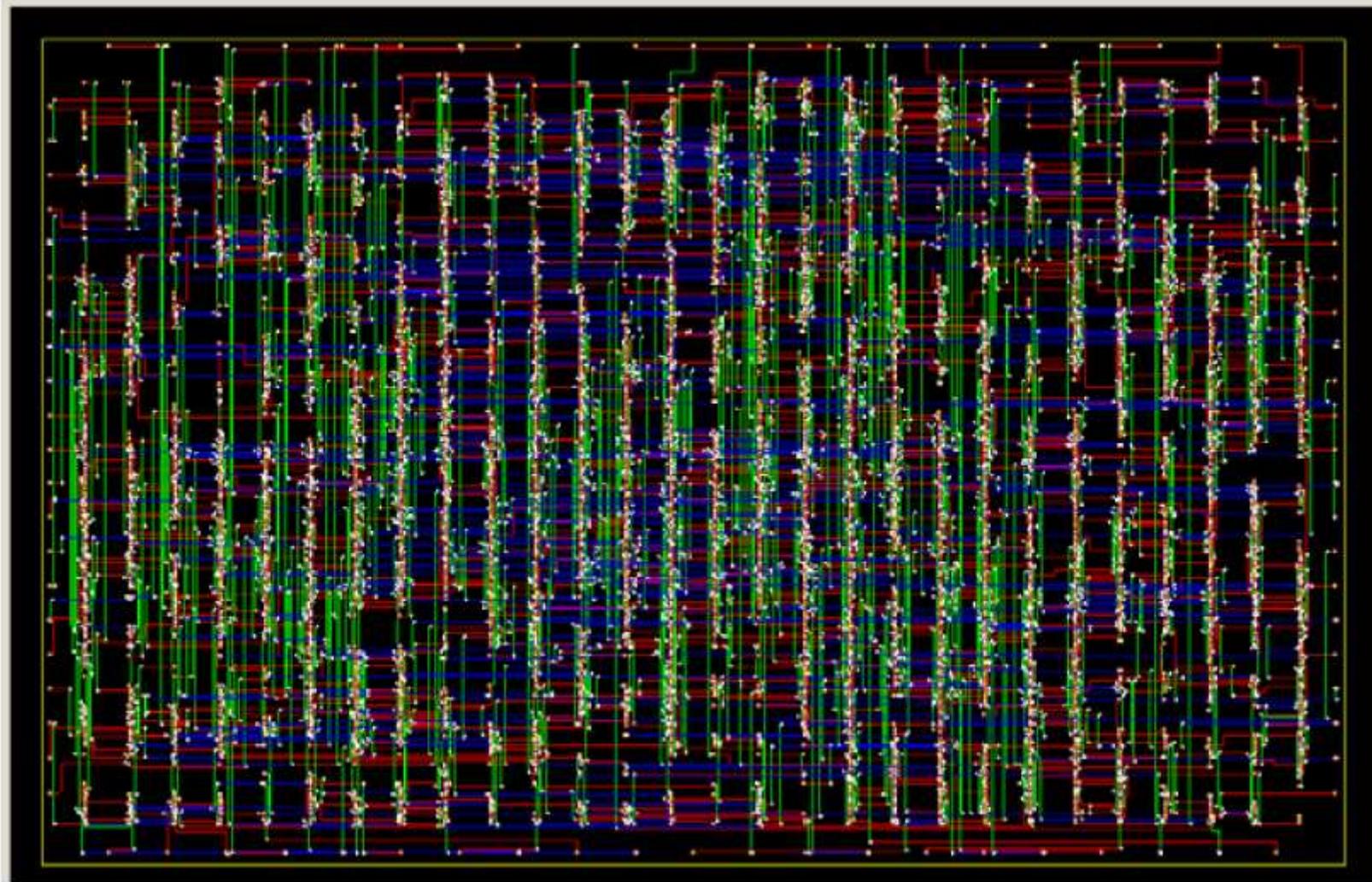




# Routing with Via Insertion Example

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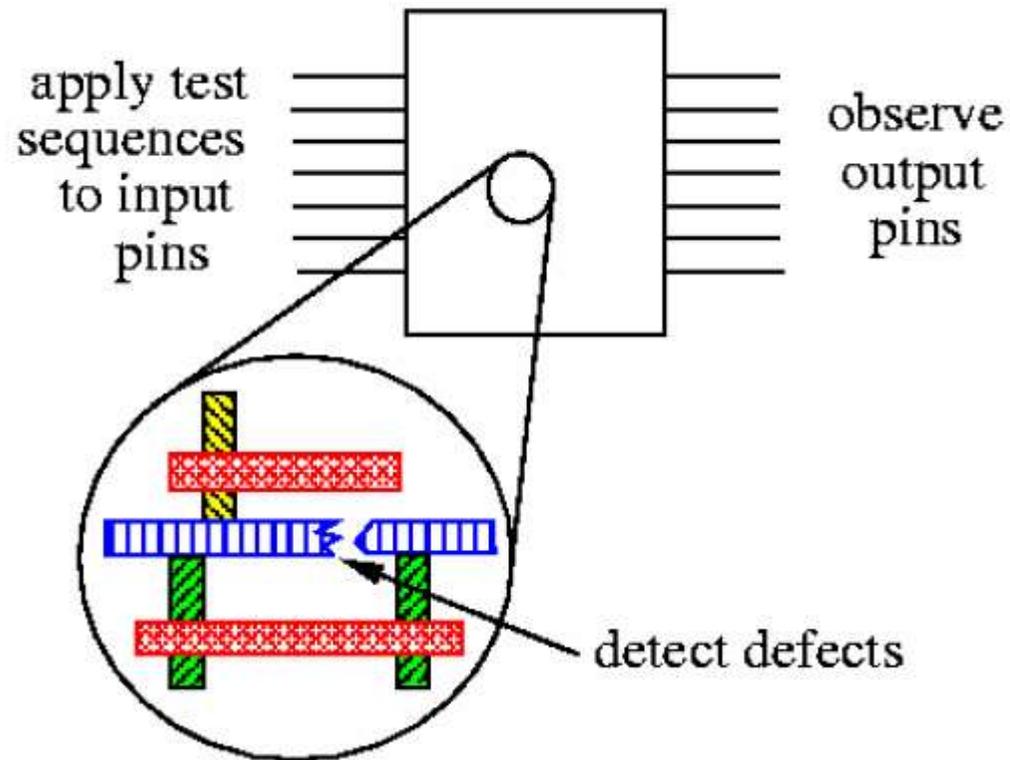
- Circuit: s5378; 3-layer, 4818 nets



# Testing

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- Verify if a design was manufactured correctly



# The Business of EDA: Introduction

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- The size of EDA industry
  - In 2002, the total revenue was about USD\$4 billion dollars
    - The semiconductor industry revenue: \$140 billion (2012 \$303 billion)
    - There were about 200 companies and about 50 different kinds of tools
- How do the EDA tools help in IC design?
  - The tools make the designers much more productive

# The Business of EDA: ROI

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- EDA **user** return on investment
  - EDA tools have a potentially huge ROI for the Original Equipment Manufacturer (OEM) electronics product companies
  - EDA tools can create big revenue gains by increasing the life of electronic products and getting to market earlier
- EDA **vendor** return on investment
  - We can typically sell a tool for anywhere from \$10K to \$200K per copy, depending on how critical it is
  - There is a large difference between the development cost and the value to the user
- Examples on the blackboard

# The Business of EDA: Business Models

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- New EDA tools adoption in design houses
  - Reference flow
- Licensing models
  - Perpetual vs. Subscription
- Mergers and acquisitions
  - Usually with lawsuits
- Application service provider model
  - Through the Internet on a usage basis, cloud model
- Design services business
  - Including selling re-usable design blocks, namely IP
  - What is the most profitable IP in the market? Guess
- Foundry services
  - Especially for physical design issues

# Existing EDA Tools Chronicles (1/2)

Year	Design Tools	Company
1950 ~ 1960	Manual design	
1965 ~ 1975	Layout editors Automatic routers (for PCB) Efficient partitioning algorithm	
1975 ~ 1985	Automatic placement tools Well defined phase of design of circuits Significant theoretical development in all phases	Applicon Calma Computervision
1985 ~ 1990	Performance driven placement and routing tools Parallel algorithms for physical design Significant development in underlying graph theory Combinatorial optimization problems for layouts	Daisy Mentor Valid

# Existing EDA Tools Chronicles (2/2)

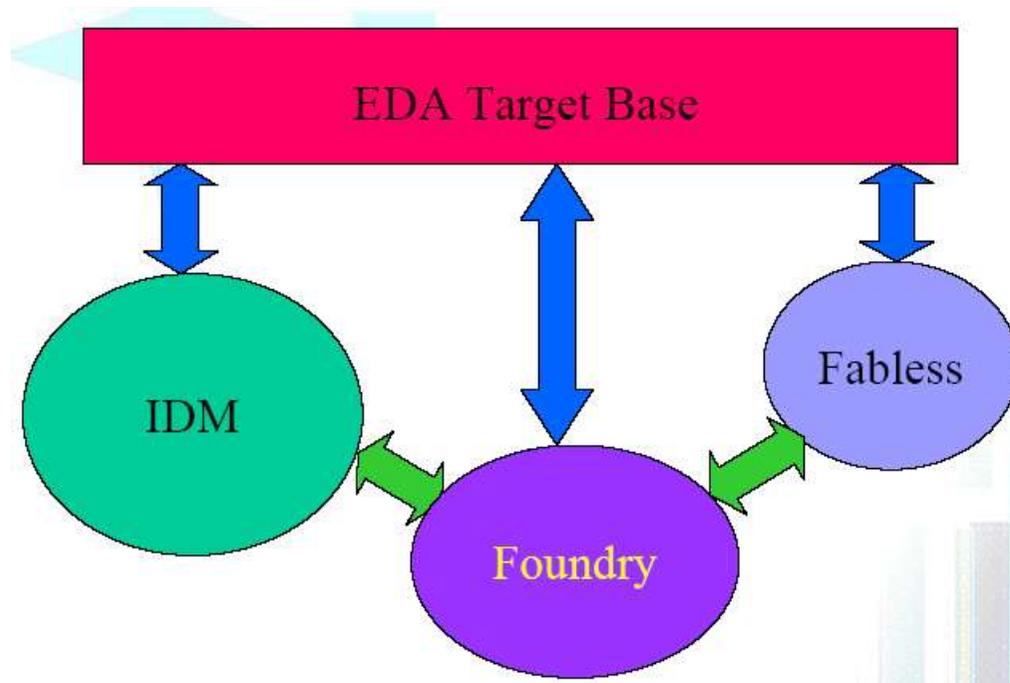
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Year	Design Tools	Company
1990 ~ 1995	Over-the-Cell Routing tools Three dimensional interconnect based physical design Synthesis tools mature and gain widespread acceptance	Avanti(Synopsys) Cadence Synopsys
1995 ~ Present	Interconnect design and Modeling dominates physical design Process related tools (reliability, electro-migration)	Magma (Synopsys) Monterey Verplex (Cadence) SPC(Cadence) Numerical (Synopsys) Springsoft (Synopsys) EverCAD (Mentor)

# IC/SoC Industry Segments in Taiwan

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- Integrated Device Manufacturers (IDM)
- Foundries
- Fabless Semiconductor Companies
- EDA Vendors



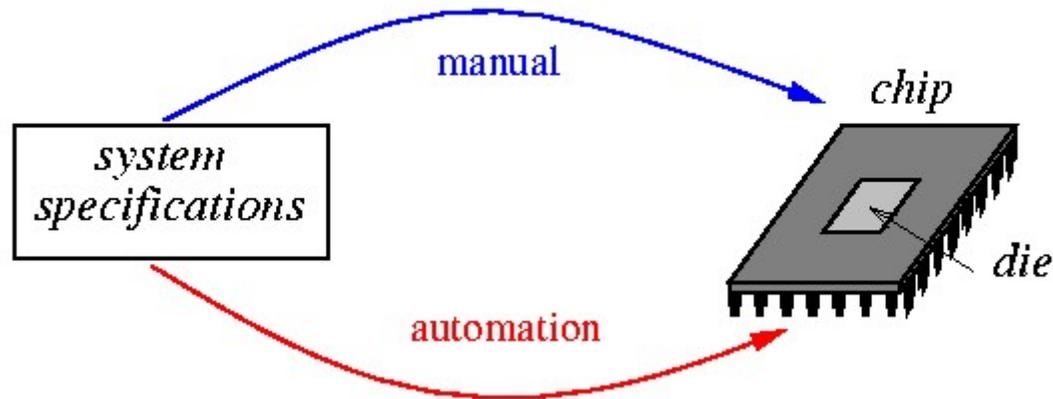
# What Techniques Do We Need in EDA Business?

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- The best of both worlds
- Software background
  - Algorithms and programming language
  - Data structures play important roles
- Hardware background
  - Device modeling
  - Interconnect modeling
  - Manufacture related issues
  - Circuit design and synthesis
- Combinatorial optimization
  - Unconstrained and constrained optimization
  - Mathematical programming
- Validation and verification techniques
  - Formal methods

# IC Design Considerations

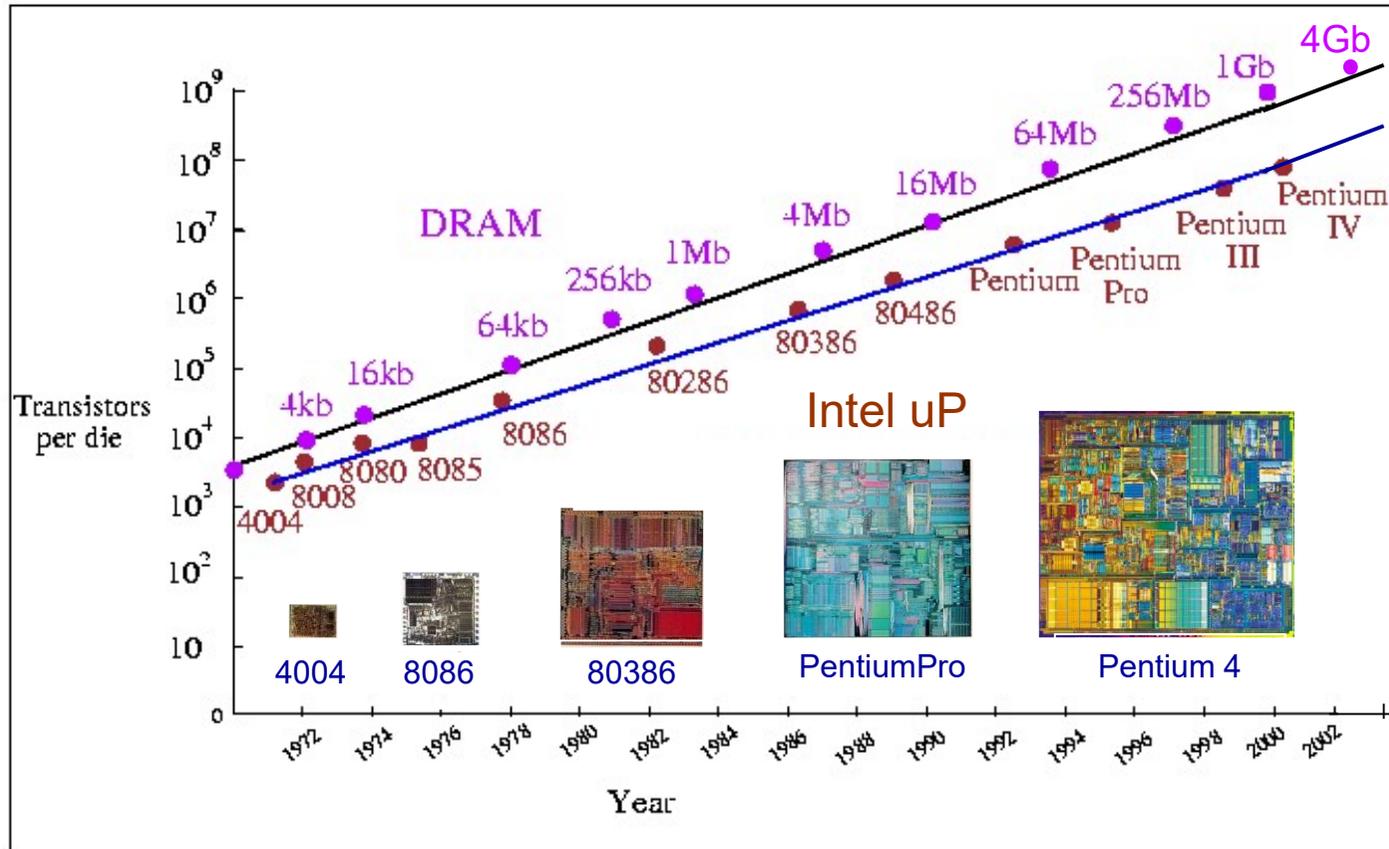
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- Several conflicting considerations:
  - **Design Complexity:** large number of devices/transistors
  - **Performance:** optimization requirements for high performance
  - **Time-to-market:** about a 15% gain for early birds
  - **Cost:** die area, packaging, testing, etc.
  - Others: power, signal integrity (noise, etc), testability, reliability, manufacturability, etc.

# “Moore’s” Law: Driving Technology Advances

- Logic capacity doubles per IC at a regular interval.
- Moore: Logic capacity doubles per IC every two years (1975).
- D. House: Computer performance doubles every 18 months (1975)



# Technology Roadmap for Semiconductors

Year	1997	1999	2002	2005	2008	2011	2014
Technology node ( <i>nm</i> )	250	180	130	100	70	50	35
On-chip local clock ( <i>GHz</i> )	0.75	1.25	2.1	3.5	6.0	10	16.9
Microprocessor chip size ( <i>mm</i> <sup>2</sup> )	300	340	430	520	620	750	901
Microprocessor transistors/chip	11M	21M	76M	200M	520M	1.40B	3.62B
Microprocessor cost/transistor ( $\times 10^{-8}$ USD)	3000	1735	580	255	110	49	22
DRAM bits per chip	256M	1G	4G	16G	64G	256G	1T
Wiring level	6	6-7	7	7-8	8-9	9	10
Supply voltage ( <i>V</i> )	1.8-2.5	1.5-1.8	1.2-1.5	0.9-1.2	0.6-0.9	0.5-0.6	0.37-0.42
Power ( <i>W</i> )	70	90	130	160	170	175	183

- Source: International Technology Roadmap for Semiconductors (ITRS), Nov. 2002. <http://www.itrs.net/ntrs/pubIntrs.nsf>.
- Deep submicron technology: node (**feature size**) < 0.25  $\mu m$ .
- Nanometer Technology: node < 0.1  $\mu m$ .

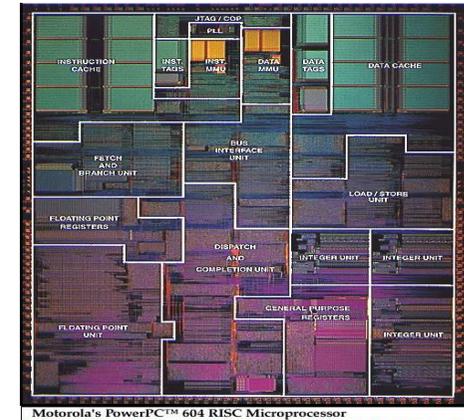
# Nanometer Design Challenges

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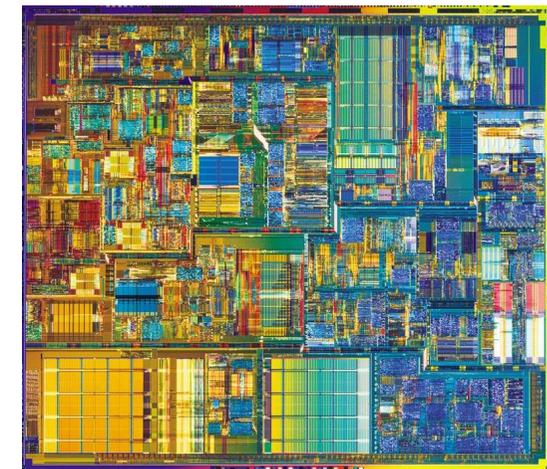
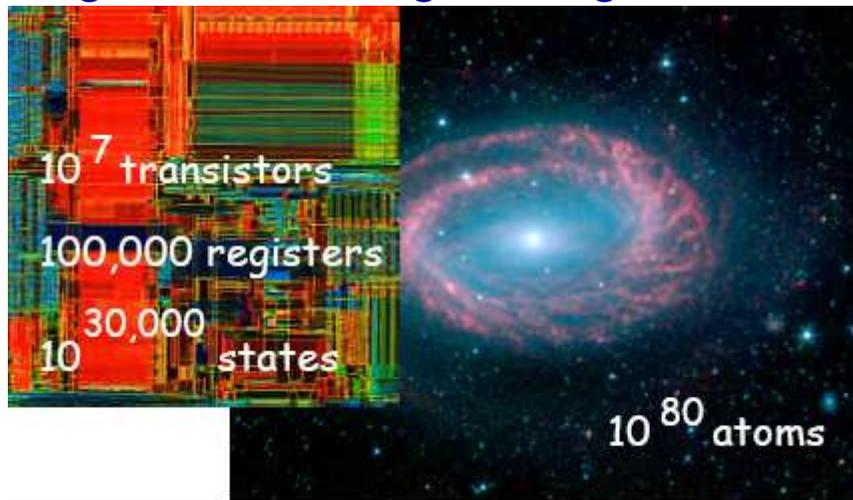
- In 2007, feature size  $\approx 65 \text{ nm}$ ,  $\mu\text{P}$  frequency  $\approx 5 \text{ GHz}$ , die size  $\approx 600 \text{ mm}^2$ ,  $\mu\text{P}$  transistor count per chip  $\approx 500\text{M}$ , wiring level  $\approx 9$  layers, supply voltage  $\approx 0.9 \text{ V}$ , power consumption  $\approx 170 \text{ W}$ .
  - **Chip complexity**
    - Effective design and verification methodology? More efficient optimization algorithms? Time-to-market?
  - **Power consumption**
    - Power & thermal issues?
  - **Supply voltage**
    - Signal integrity (noise, IR drop, etc)?
  - **Feature size, dimension**
    - Sub-wavelength lithography (impacts of process variation)? noise? wire coupling? reliability? manufacturability? 3D layout?
  - **Frequency**
    - Interconnect delay? electromagnetic field effects? Timing closure?

# Design Complexity Increases Dramatically!!

- Design issues
  - Design space exploration
  - More efficient optimization algorithms
- Verification issues
  - State explosion problem
  - For modern designs, about 60%-80% of the overall design time was spent on verification; 3-to-1 head count ratio between verification engineers and logic designers



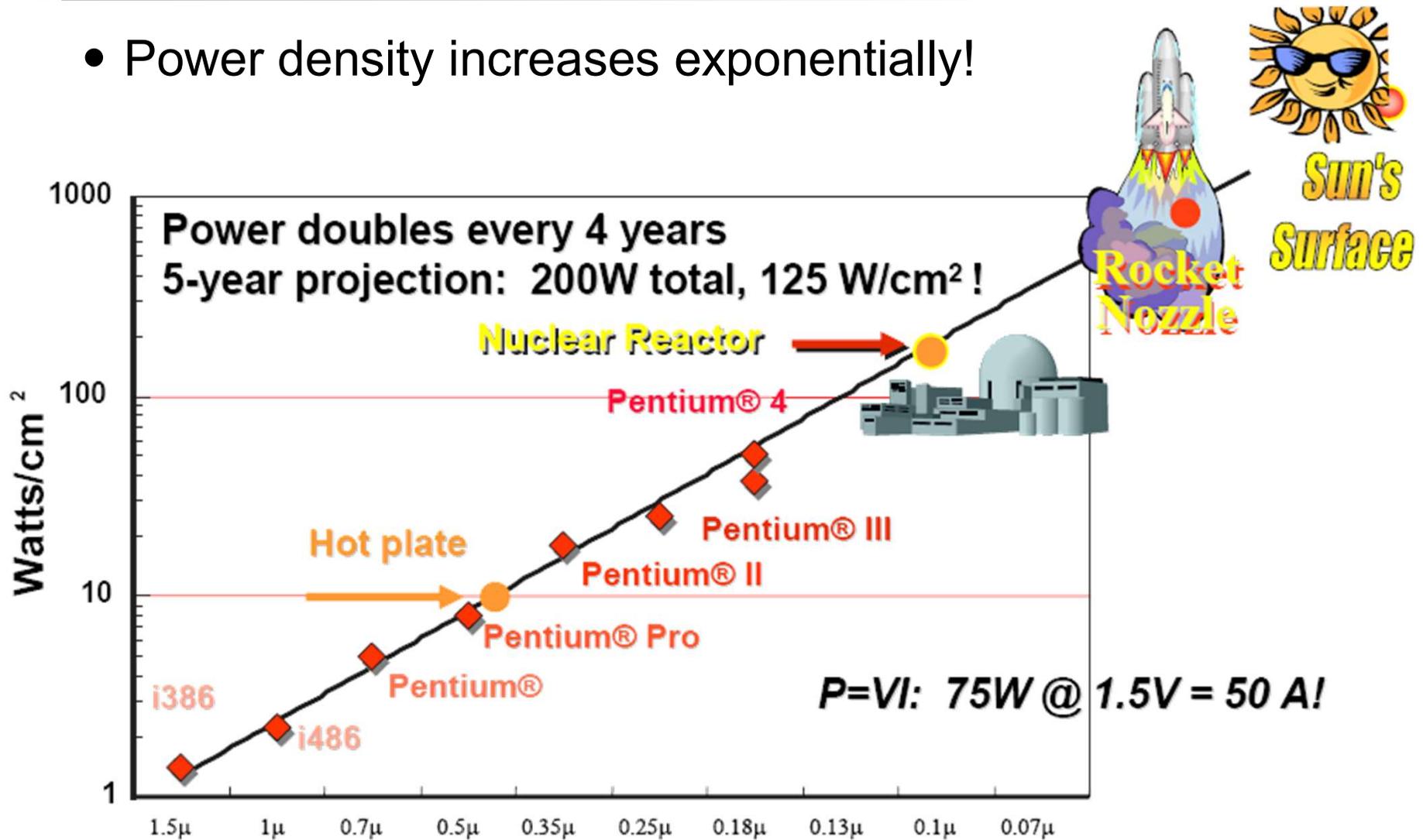
PowerPC 604



Intel Pentium 4

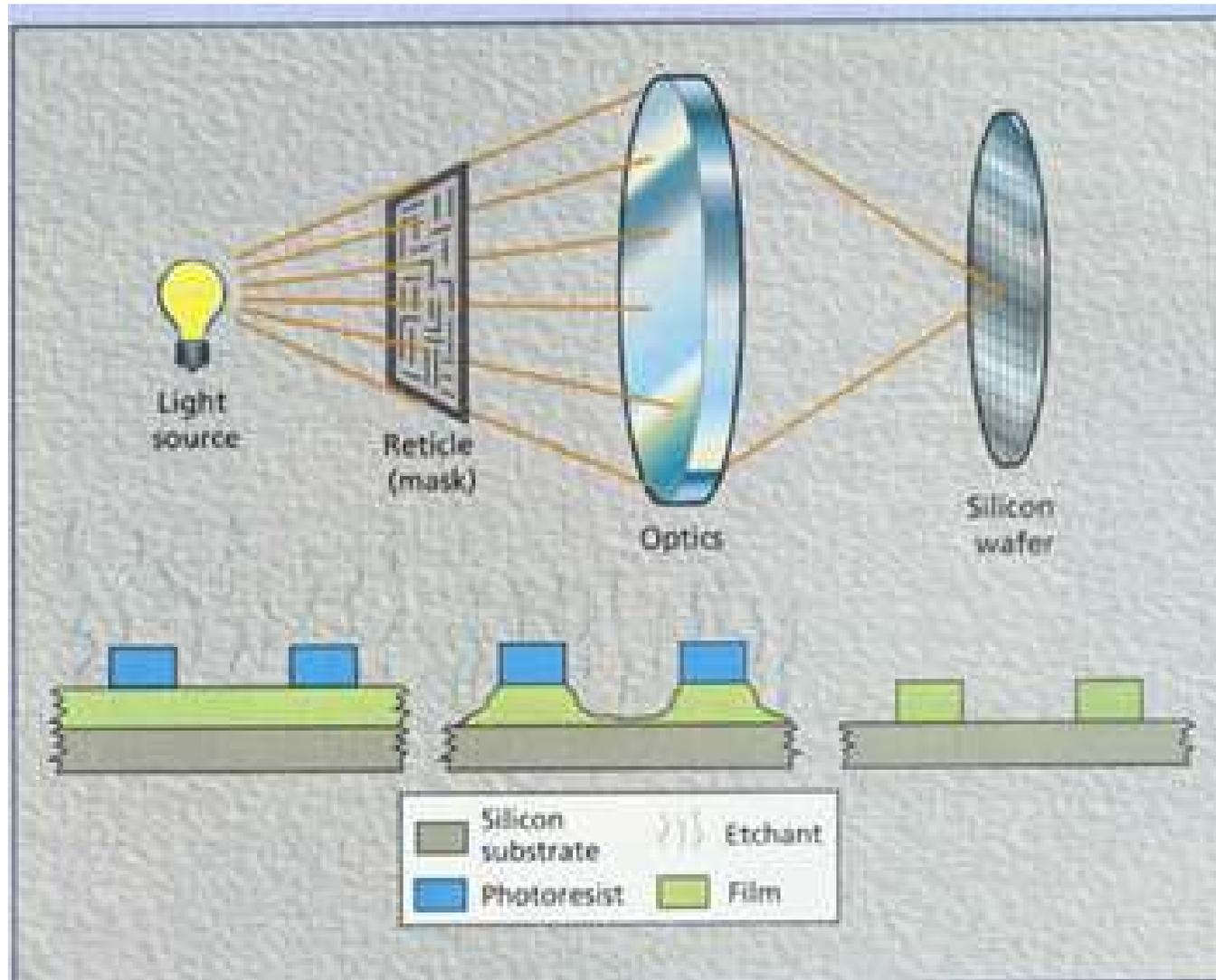
# Power/Thermal Is Another Big Problem!!

- Power density increases exponentially!



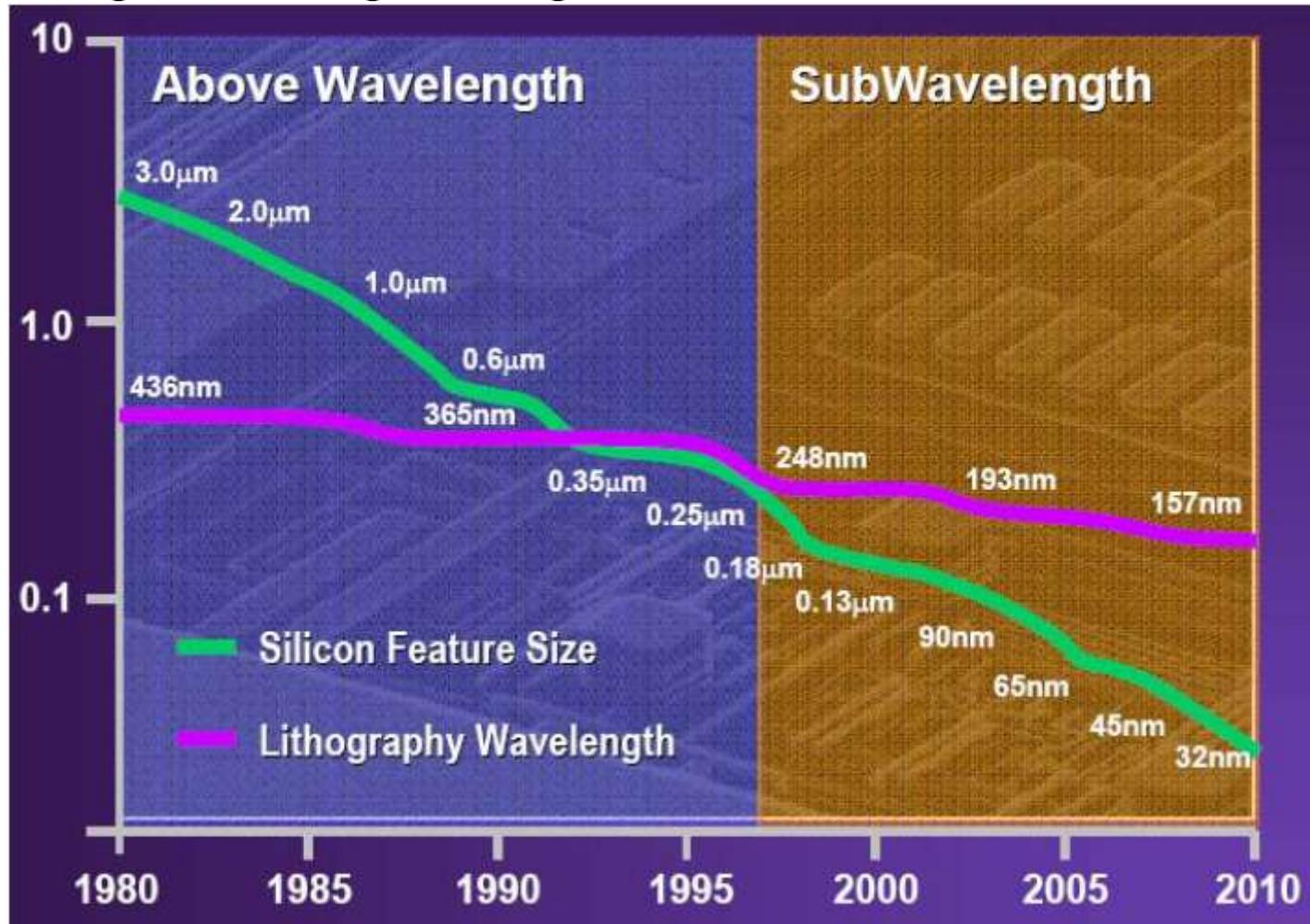
Fred Pollack, "New Microarchitecture Challenges in the Coming Generations of CMOS Process Technologies," 1999 Micro32 Conference keynote. Courtesy Avi Mendelson, Intel.

# Lithography Process



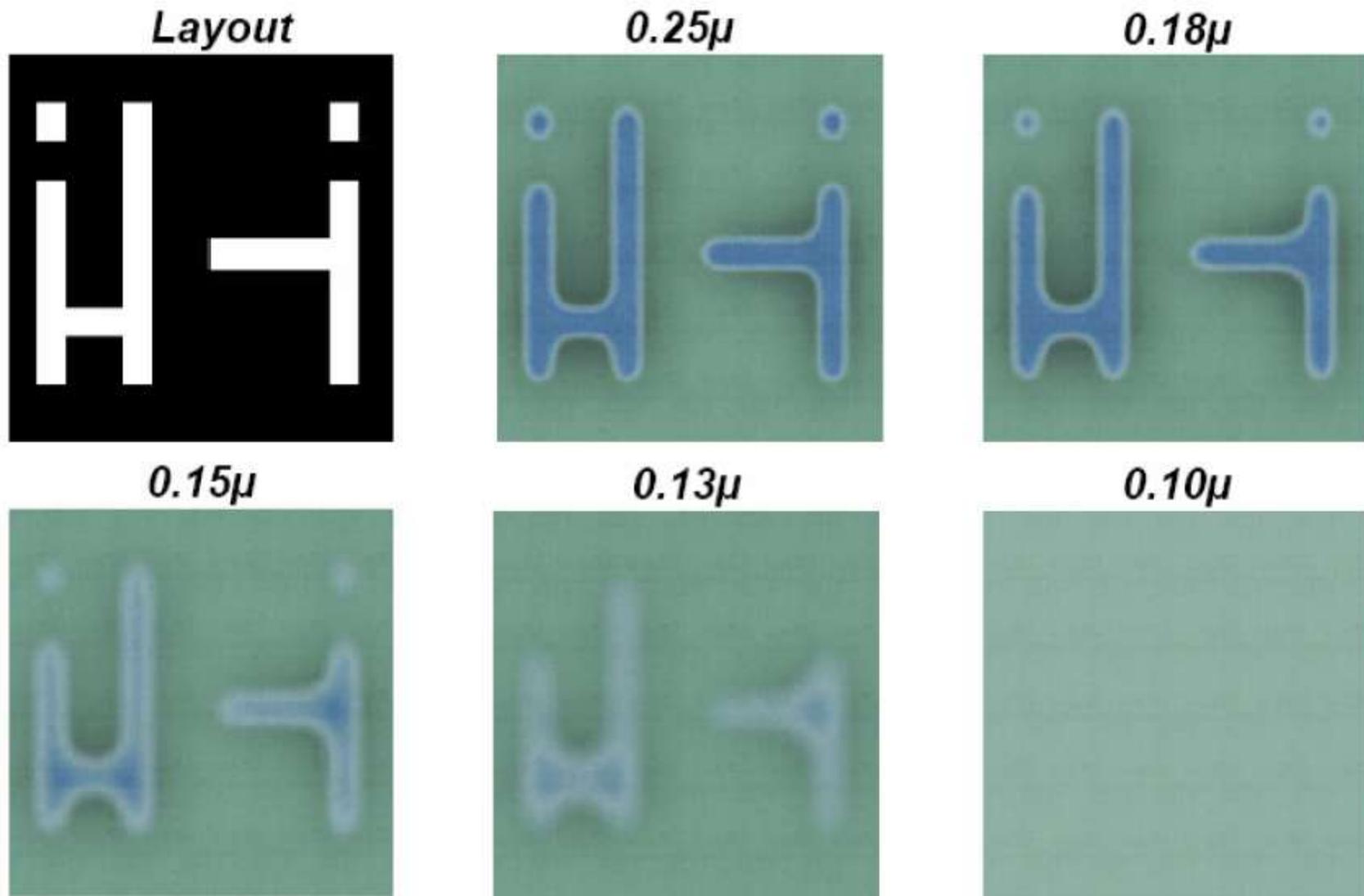
# Subwavelength Lithography Gap

- Printed feature size is smaller than the wavelength of the light shining through the mask



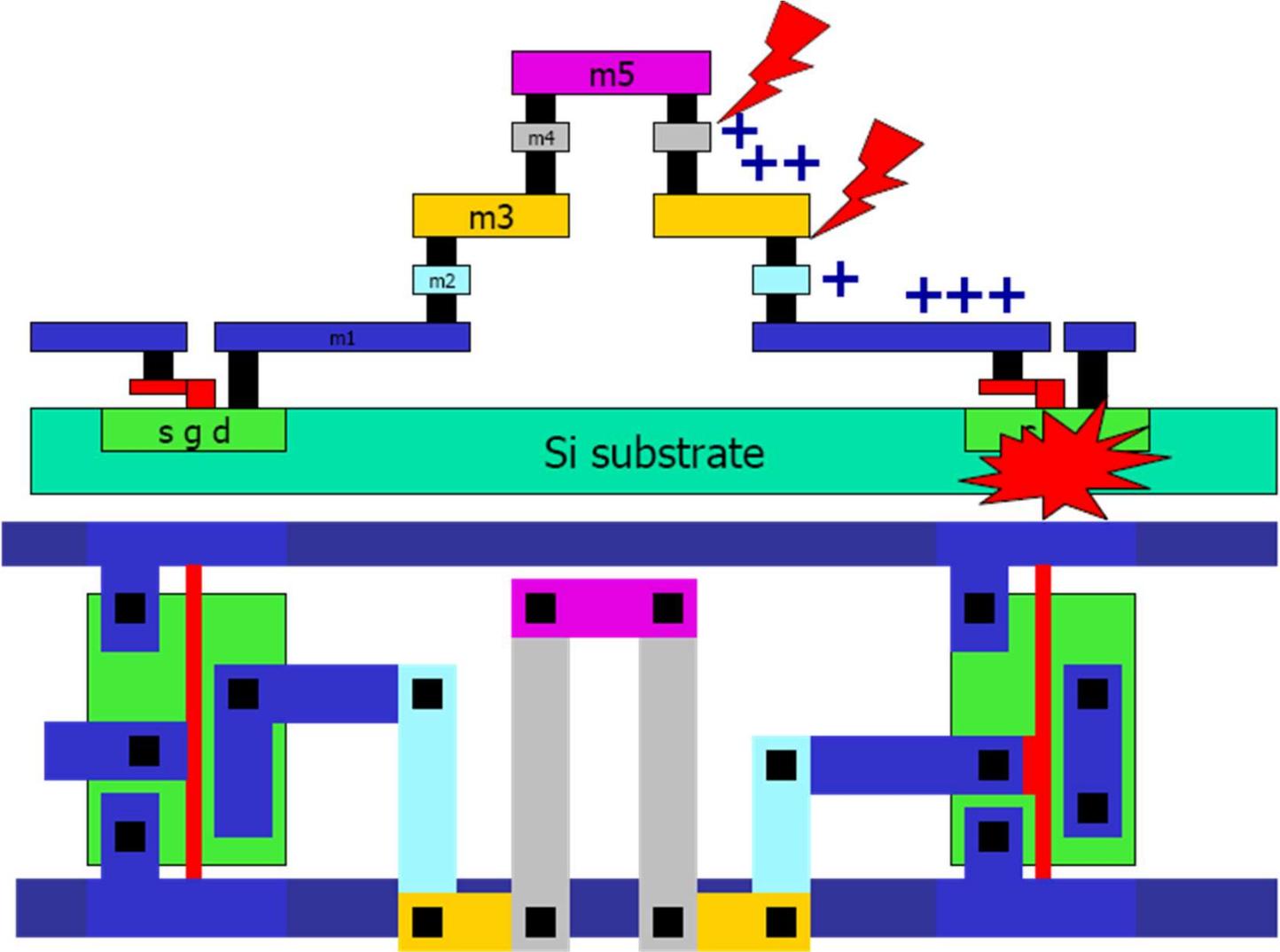
# Tale of Disappearing Silicon

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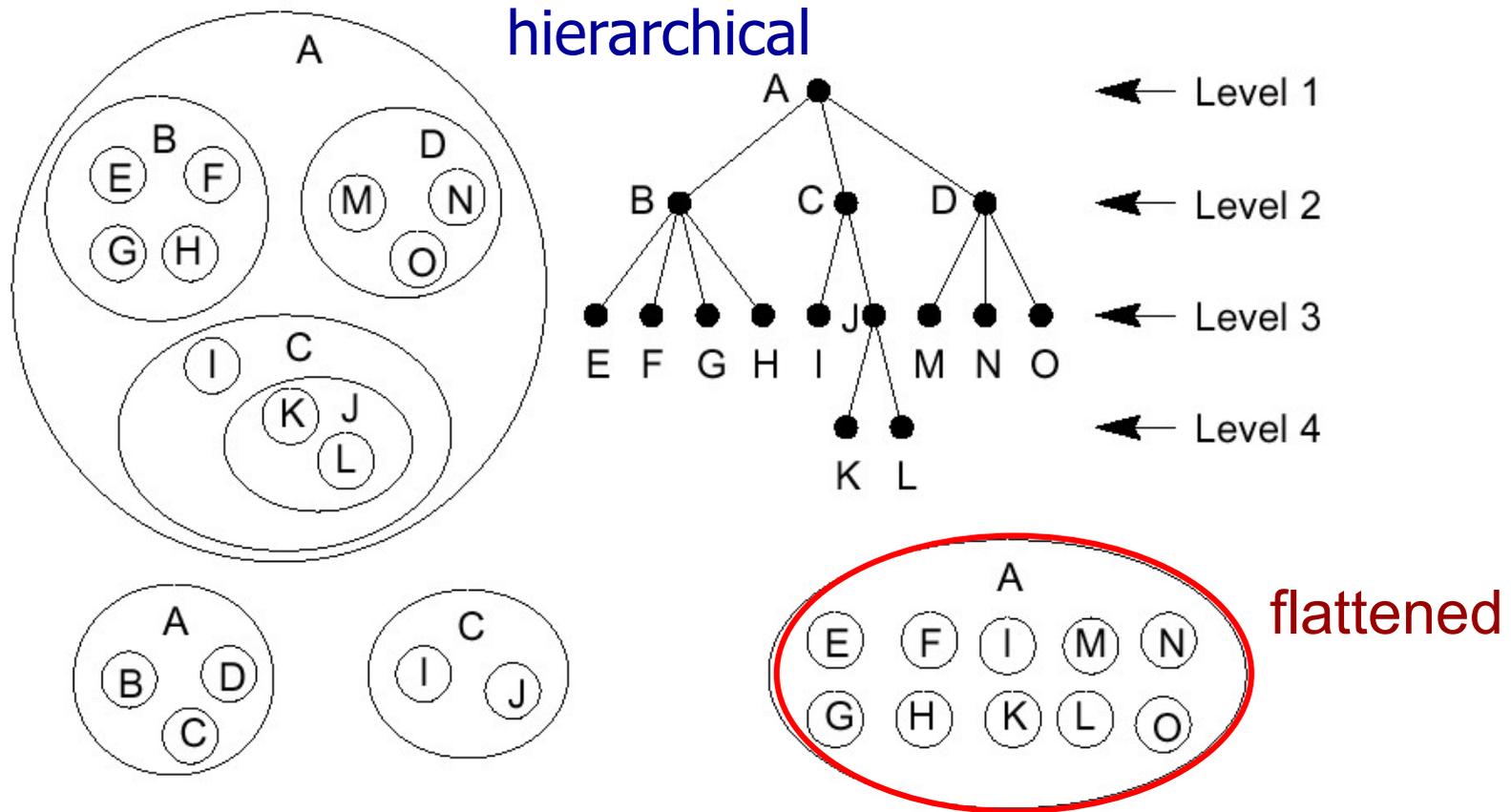
# Manufacturability Becomes a 1st-Order Effect!!

- Manufacturability and reliability with 9-layer metal?



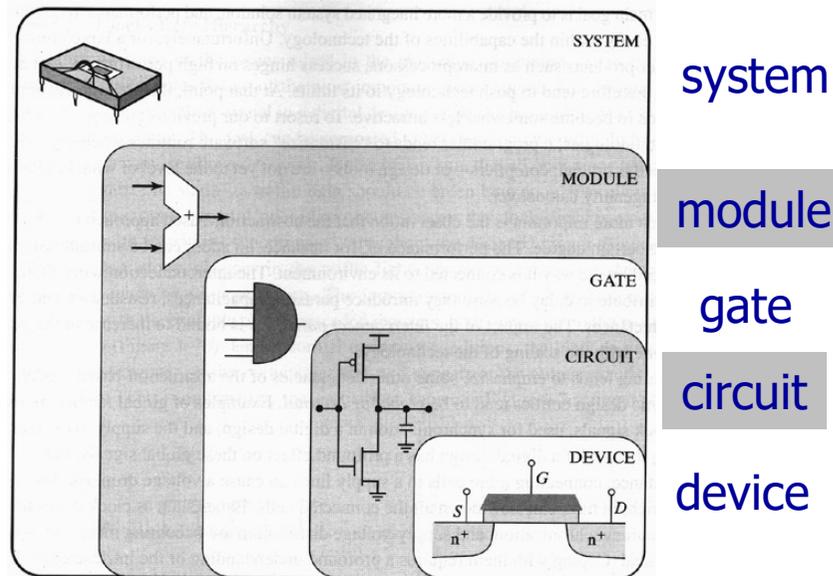
# Go Back to Design

- *Hierarchy*: something is composed of simpler things.
- Design cannot be done in one step  $\Rightarrow$  partition the design hierarchically.



# Abstraction

- **Abstraction:** when looking at a certain level, you don't need to know all details of the lower levels.



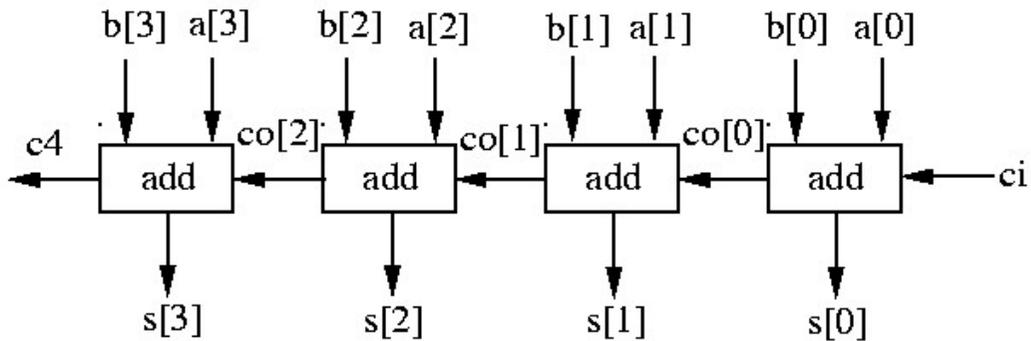
- Design domains:
  - **Behavioral:** functionality of components
  - **Structural:** connectivity between components
  - **Physical:** layout description
- Each design domain has its own hierarchy.

# Three Design Views

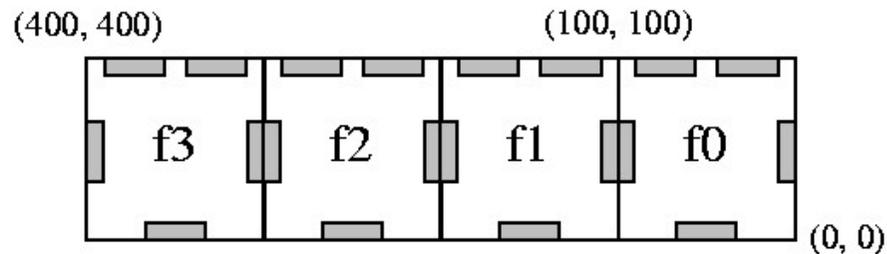
## Behavior

```
Module add4 (s, c4, ci, a, b);  
  input [3:0] a, b;  
  input ci;  
  output [3:0] s;  
  output c4;  
  assign {c4,s} = a + b + ci;  
endmodule
```

## Structural



## Physical



# Gajski's Y-Chart

---

## BEHAVIORAL DOMAIN

Systems ●  
Algorithms ●  
Register transfers ●  
Logic ●  
Transfer functions ●

## STRUCTURAL DOMAIN

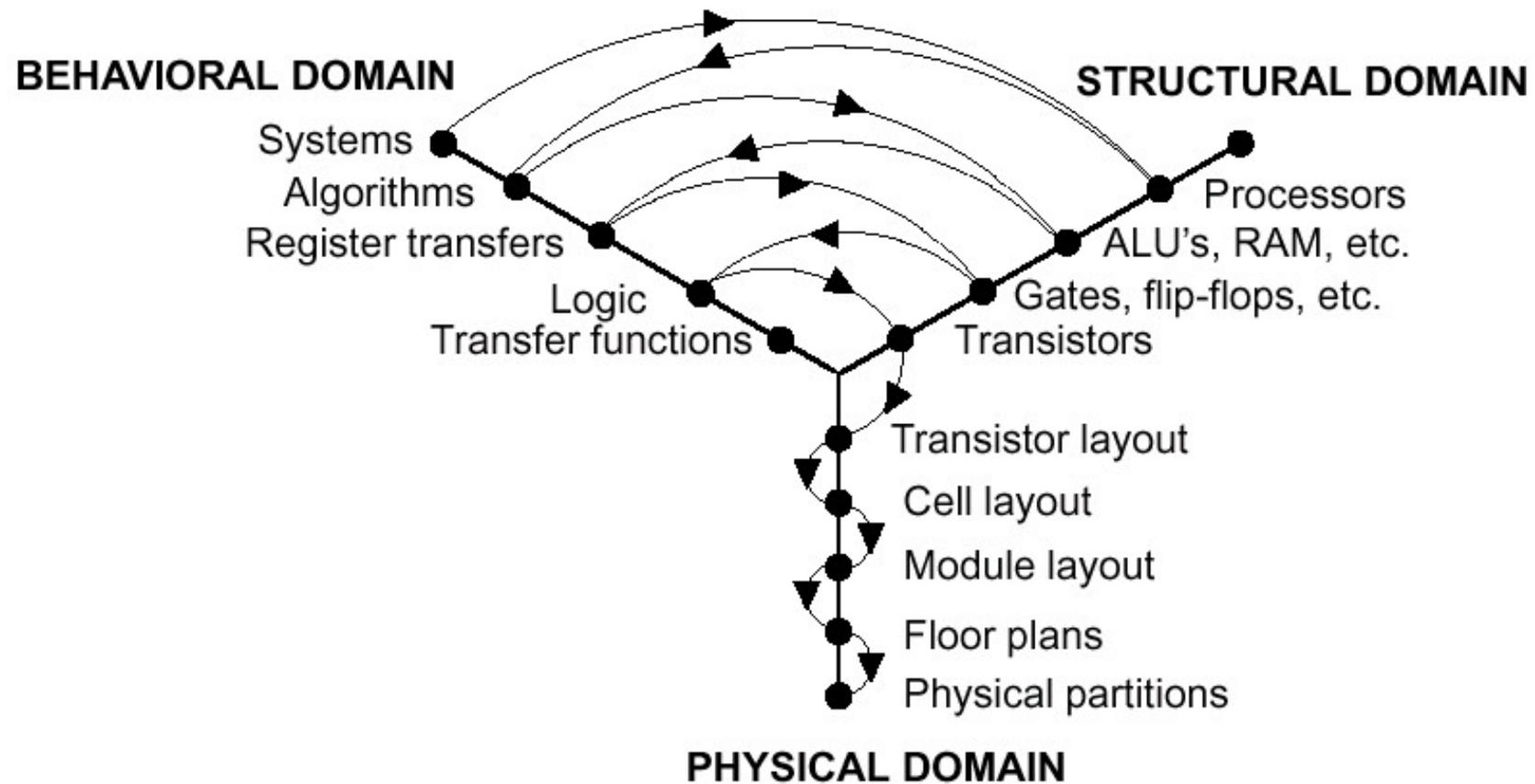
Processors ●  
ALU's, RAM, etc. ●  
Gates, flip-flops, etc. ●  
Transistors ●

● Transistor layout  
● Cell layout  
● Module layout  
● Floor plans  
● Physical partitions

## PHYSICAL DOMAIN

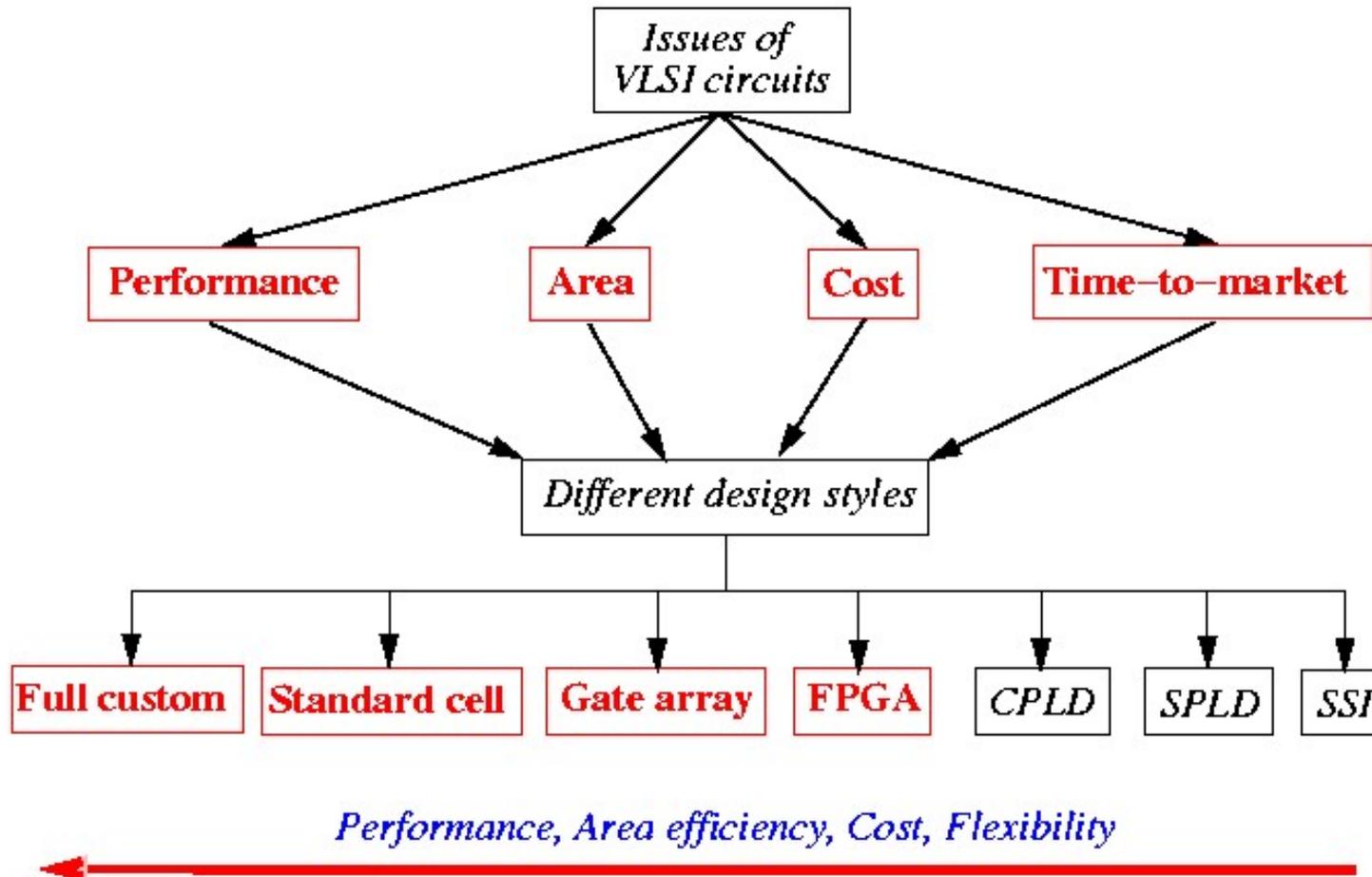
# Top-Down Structural Design

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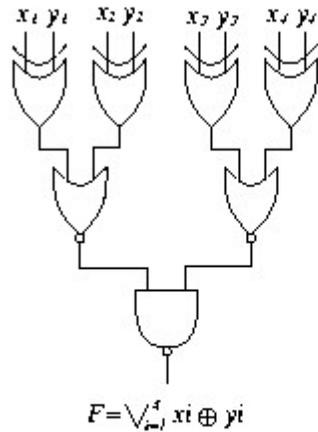


# Design Styles

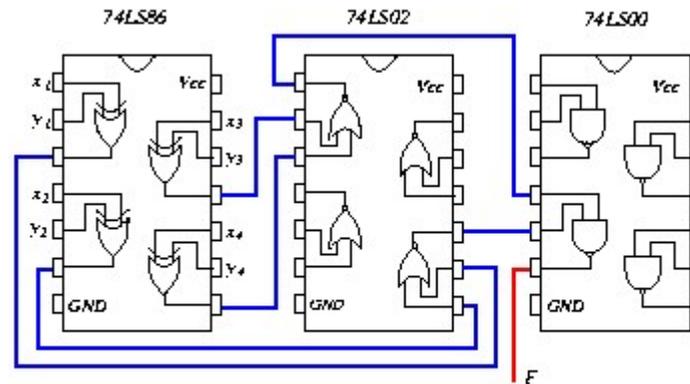
- Specific design styles shall require specific CAD tools



# SSI/SPLD Design Style

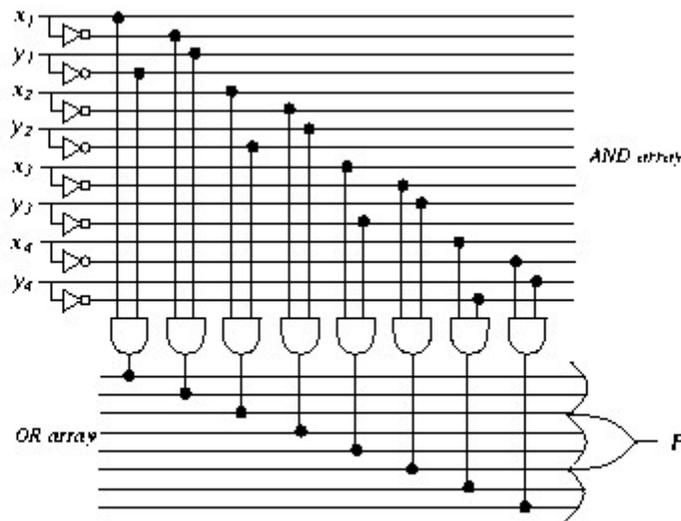


(a) 4-bit comparator.



(b) SSI implementation.

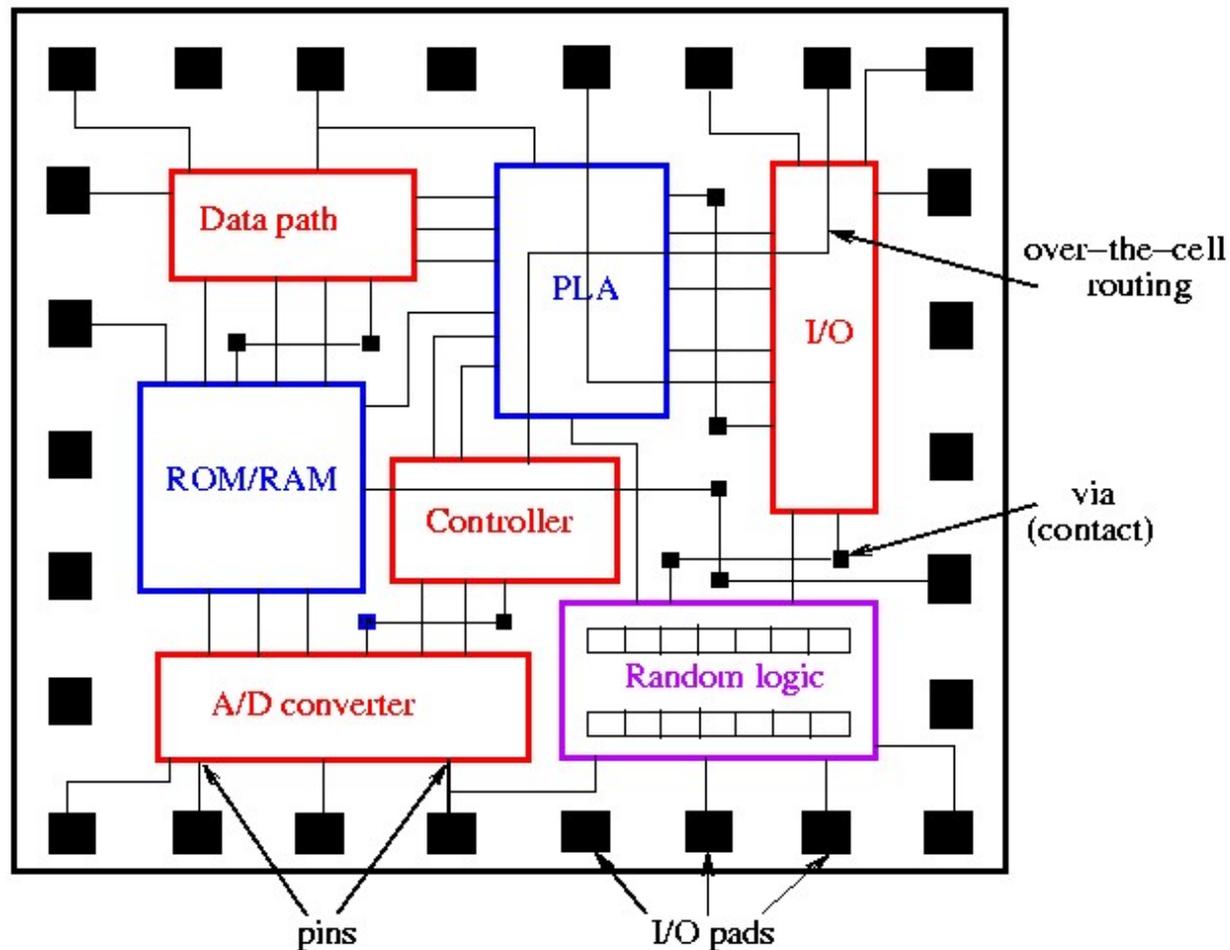
SSI: Small Scaled Integrated circuits



(c) SPLD (PLA) implementation.

# Full Custom Design Style

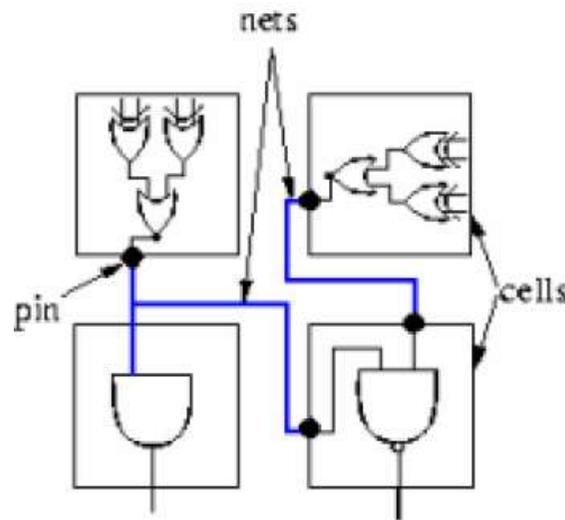
- Designers can control the shape of all mask patterns.
- Designers can specify the design up to the level of individual transistors.



# Terminology

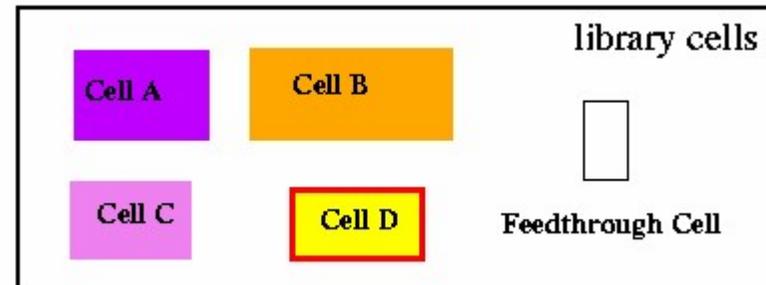
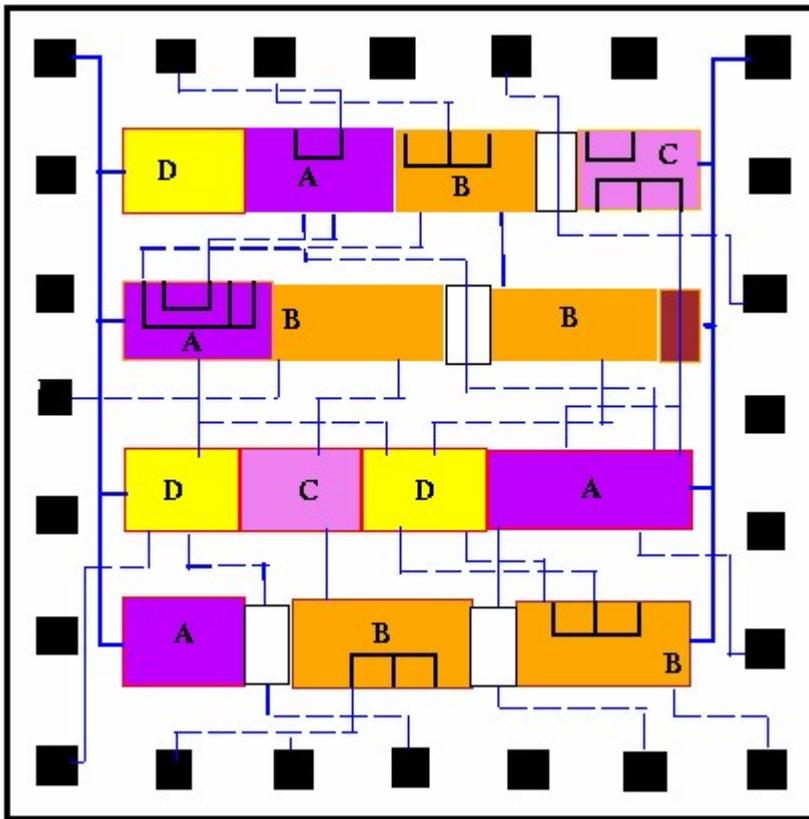
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- **Cell:** a logic block used to build larger circuits.
- **Pin:** a wire (metal or polysilicon) to which another external wire can be connected.
- **Nets:** a collection of pins which must be electrically connected.
- **Netlist:** a list of all nets in a circuit.



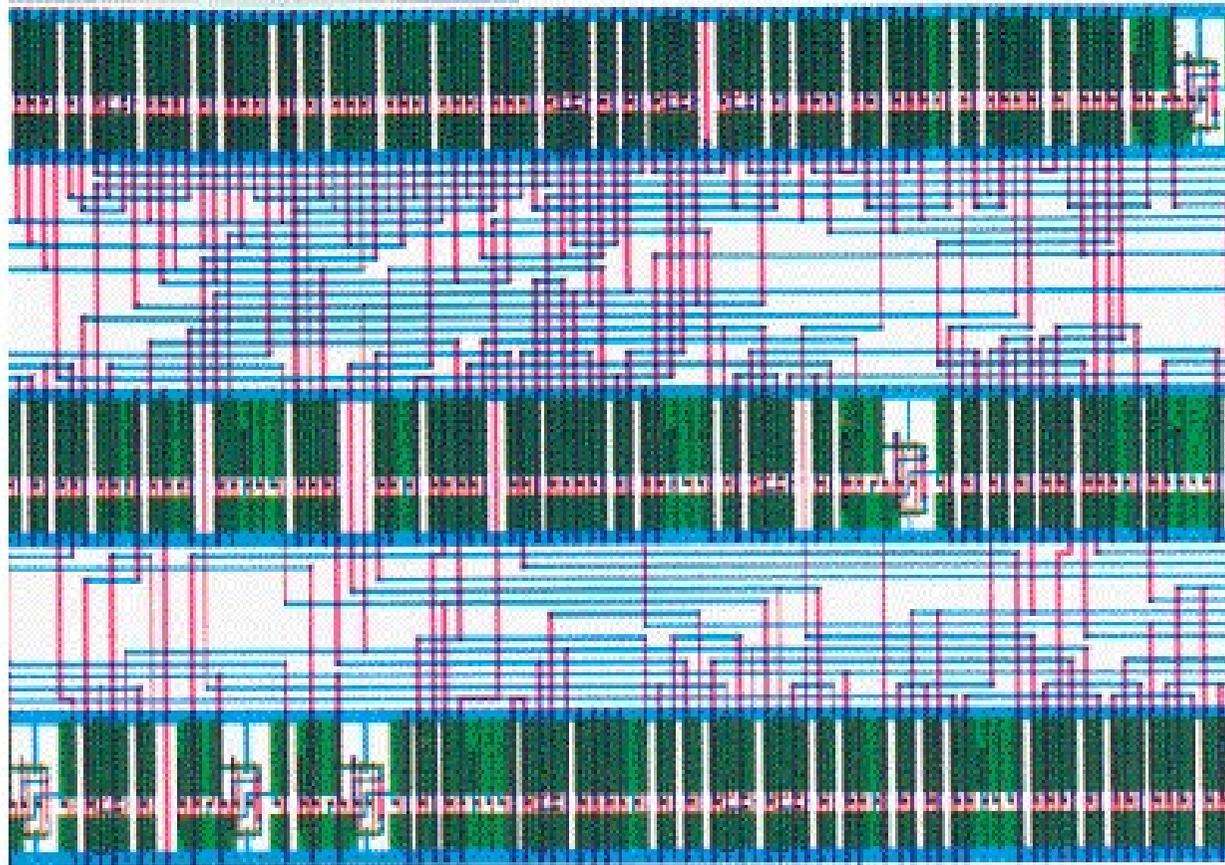
# Standard Cell Design Style

- Select pre-designed cells (of same height) to implement logic
- Characterize and store cells in library



# Standard Cell Example

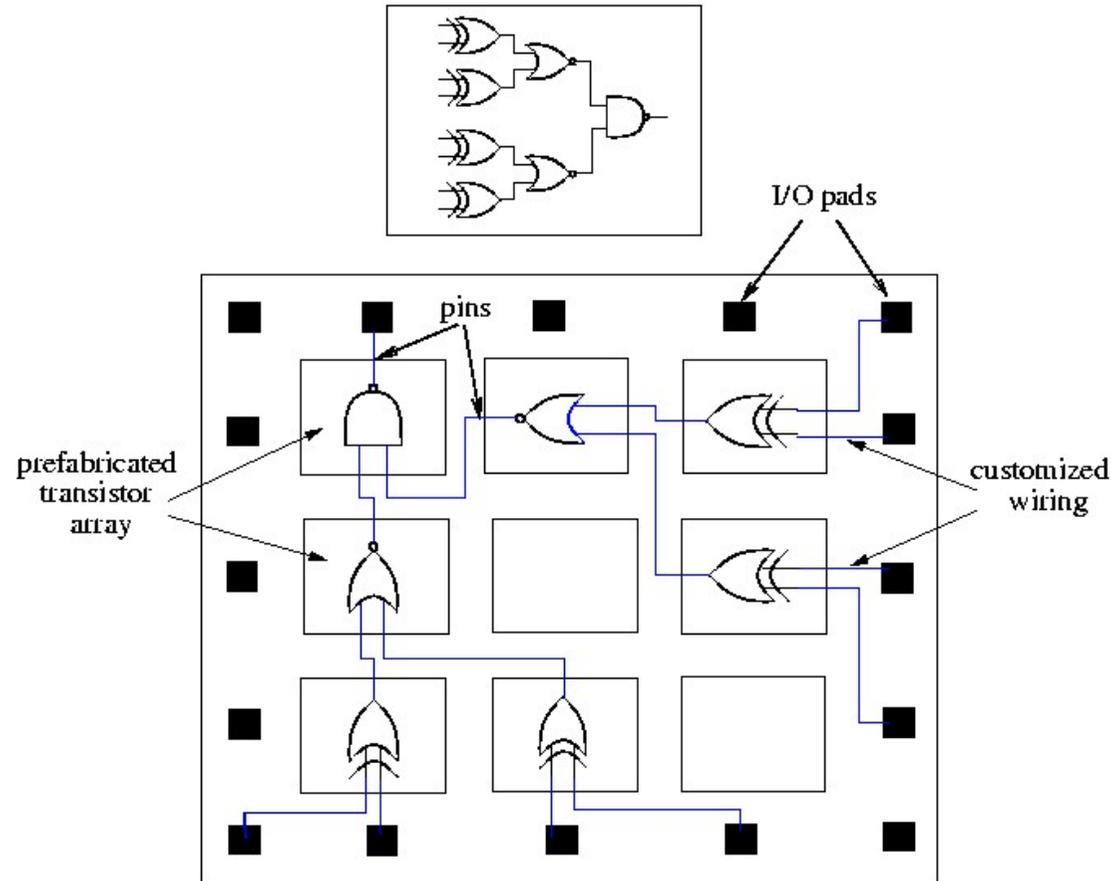
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Courtesy Newton/Pister, UC-Berkeley

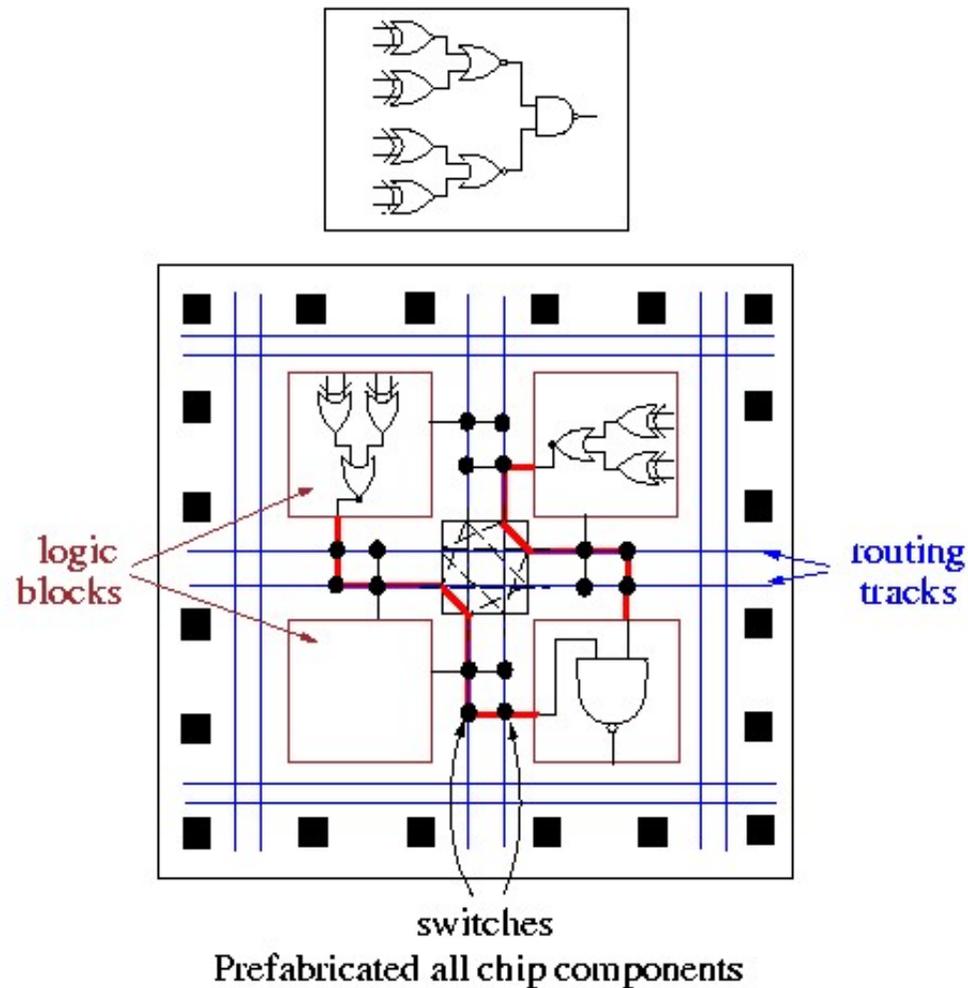
# Gate Array Design Style

- Prefabricates a transistor array
- Needs wiring customization to implement logic



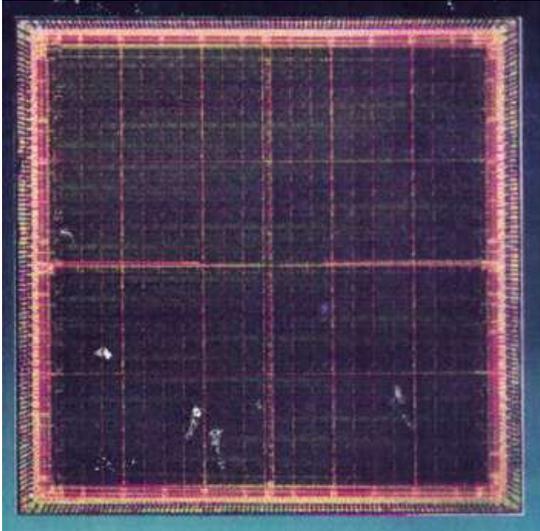
# FPGA Design Style

- Logic and interconnects are both prefabricated
- Illustrated by a symmetric array-based FPGA



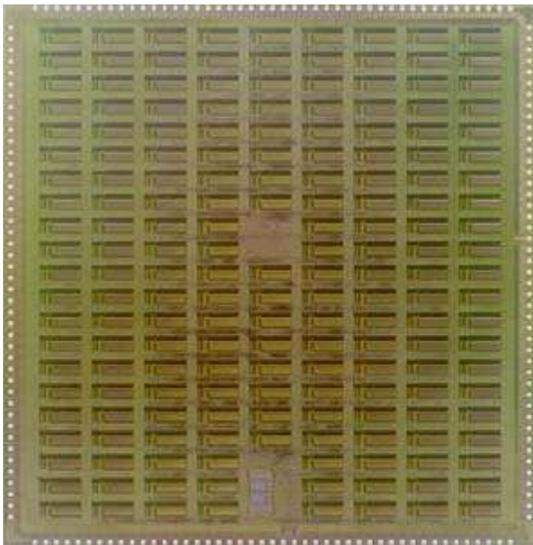
# Array-Based FPGA Example

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Lucent Technologies 15K ORCA FPGA, 1995

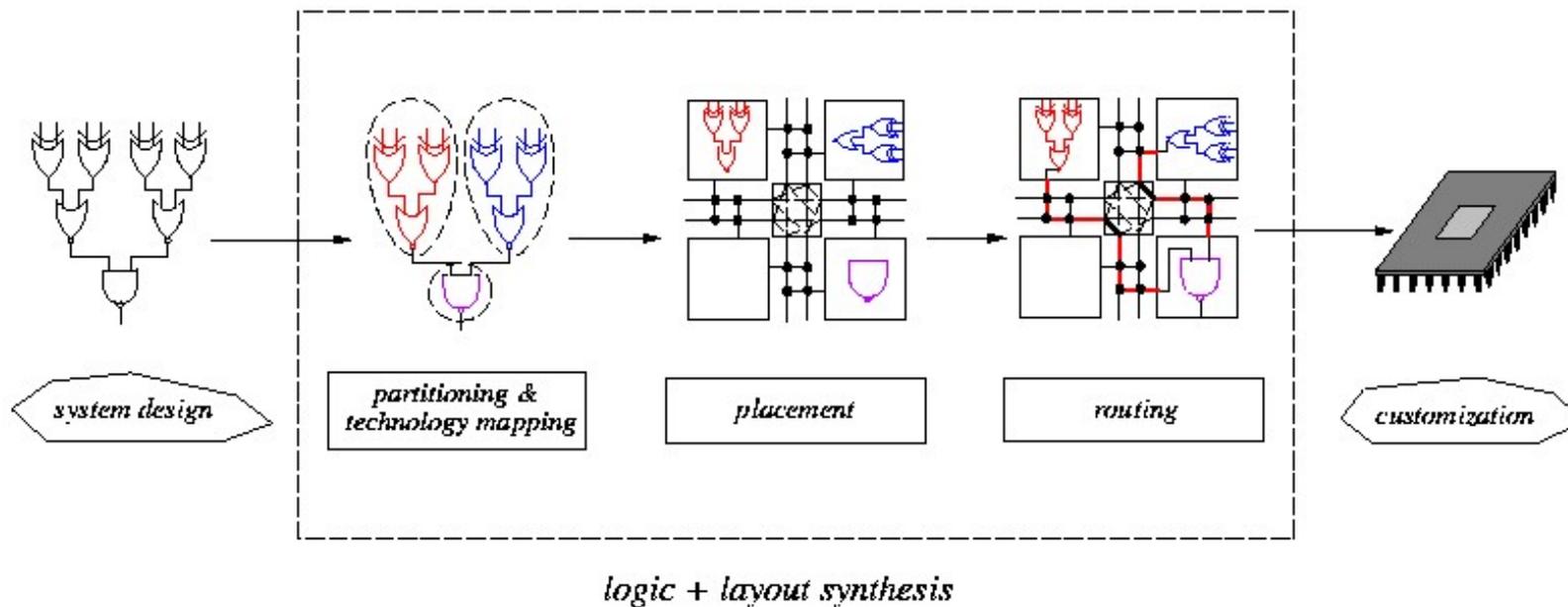
- 0.5  $\mu\text{m}$  3LM CMOS
- 2.45 M Transistors
- 1600 Flip-flops
- 25K bit user RAM
- 320 I/Os



Fujitsu's non-volatile Dynamically Programmable Gate Array (DPGA), 2002

# FPGA Design Process

- Illustrated by a symmetric array-based FPGA
- No fabrication is needed



# Comparisons of Design Styles

---

	Full custom	Standard cell	Gate array	FPGA	SPLD
Cell size	variable	fixed height*	fixed	fixed	fixed
Cell type	variable	variable	fixed	programmable	programmable
Cell placement	variable	in row	fixed	fixed	fixed
Interconnections	variable	variable	variable	programmable	programmable

\* Uneven height cells are also used.

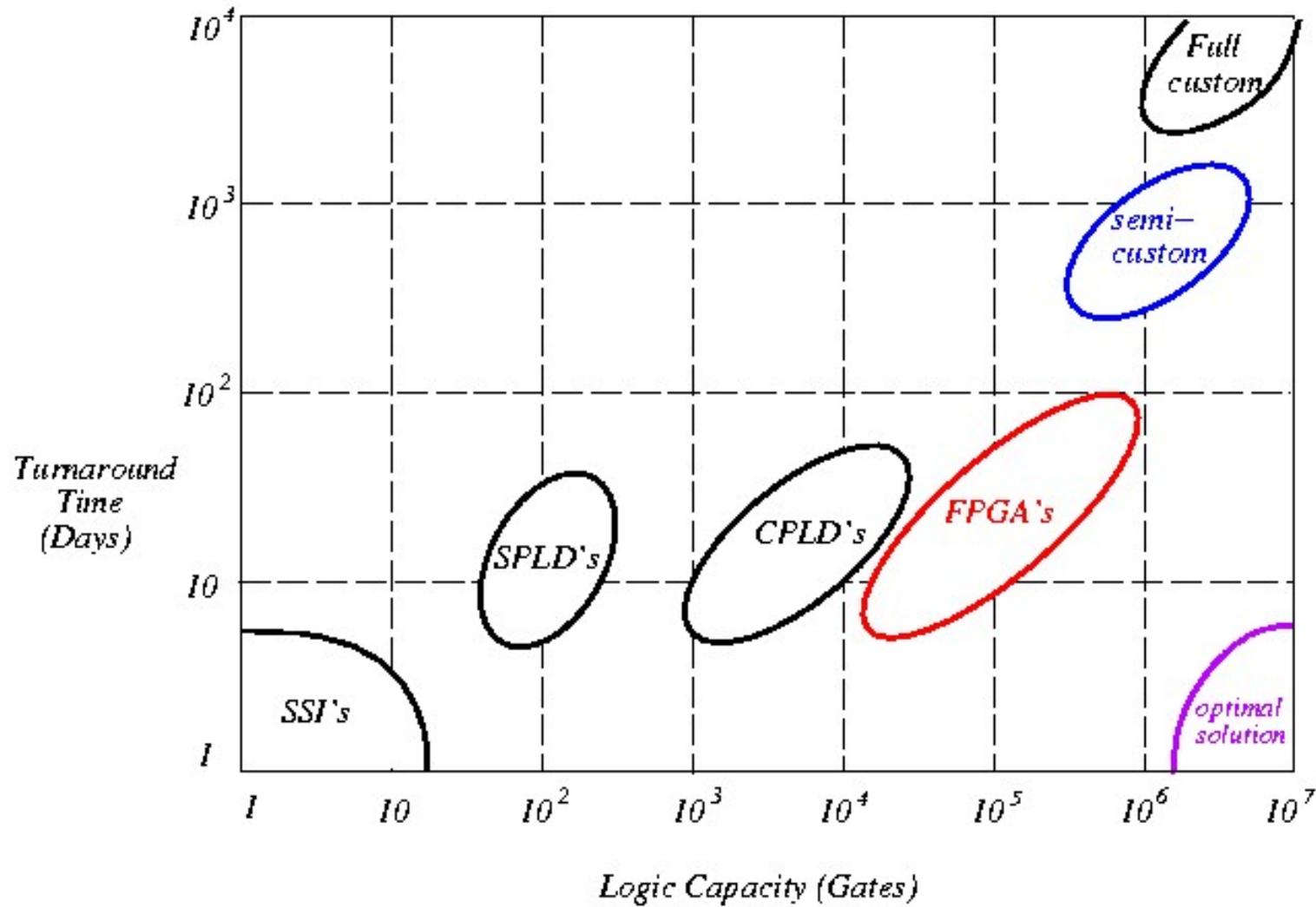
# Comparisons of Design Styles

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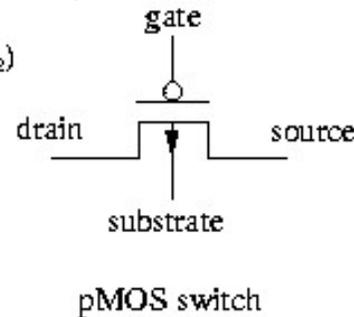
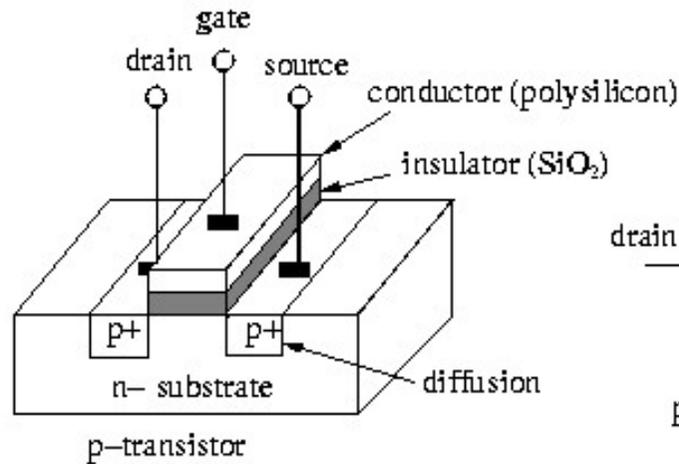
	Full custom	Standard cell	Gate array	FPGA	SPLD
Fabrication time	---	--	+	+++	++
Packing density	+++	++	+	--	---
Unit cost in large quantity	+++	++	+	--	-
Unit cost in small quantity	---	--	+	+++	++
Easy design and simulation	---	--	-	++	+
Easy design change	---	--	-	++	++
Accuracy of timing simulation	-	-	-	+	++
Chip speed	+++	++	+	-	--

+ desirable; - not desirable

# Design Style Trade-offs

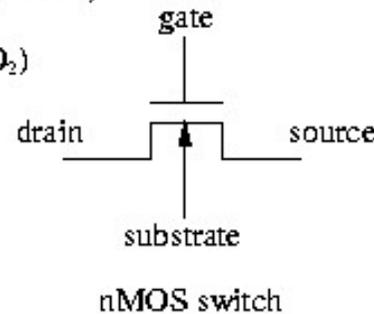
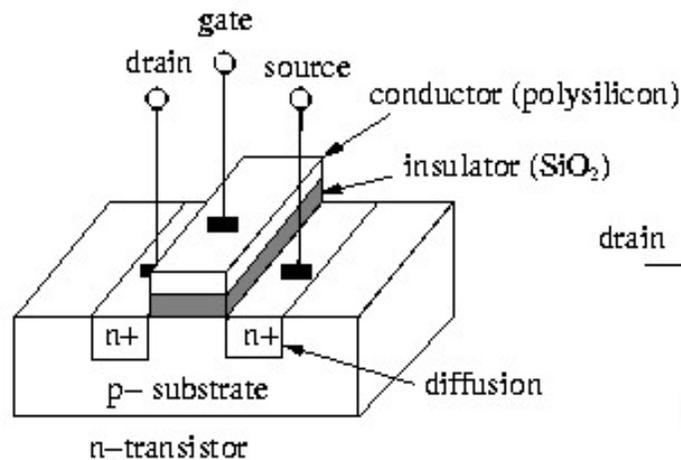


# MOS Transistors



- control input: gate
- switch terminals: drain, source (physically equivalent)
- apply zero voltage to gate  $\implies$  switch ON

**The pMOS switch passes signal "1" well.**

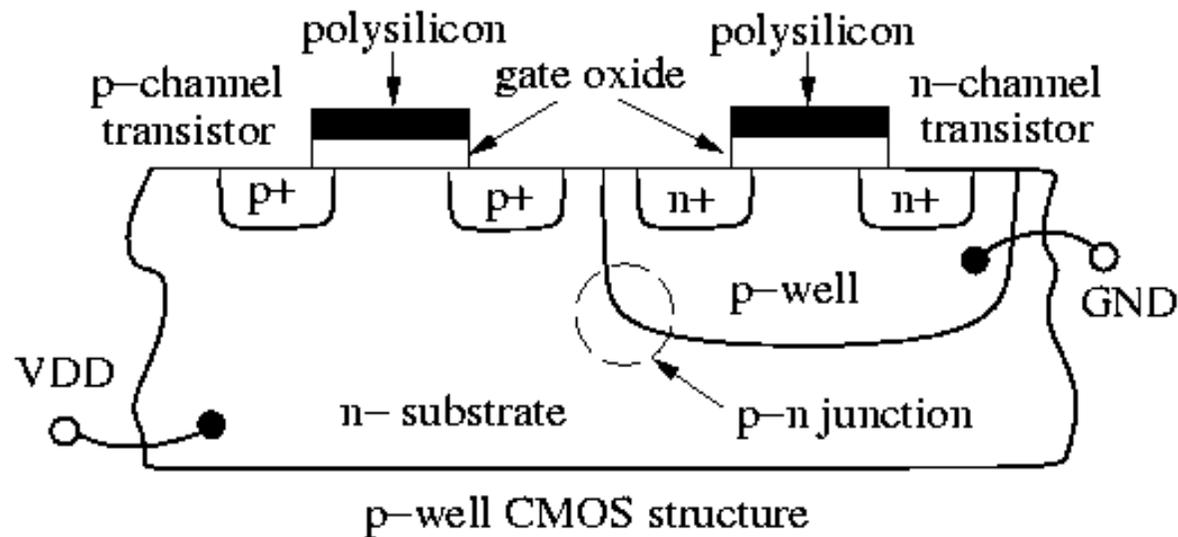


- apply  $>$  threshold voltage to gate  $\implies$  switch ON

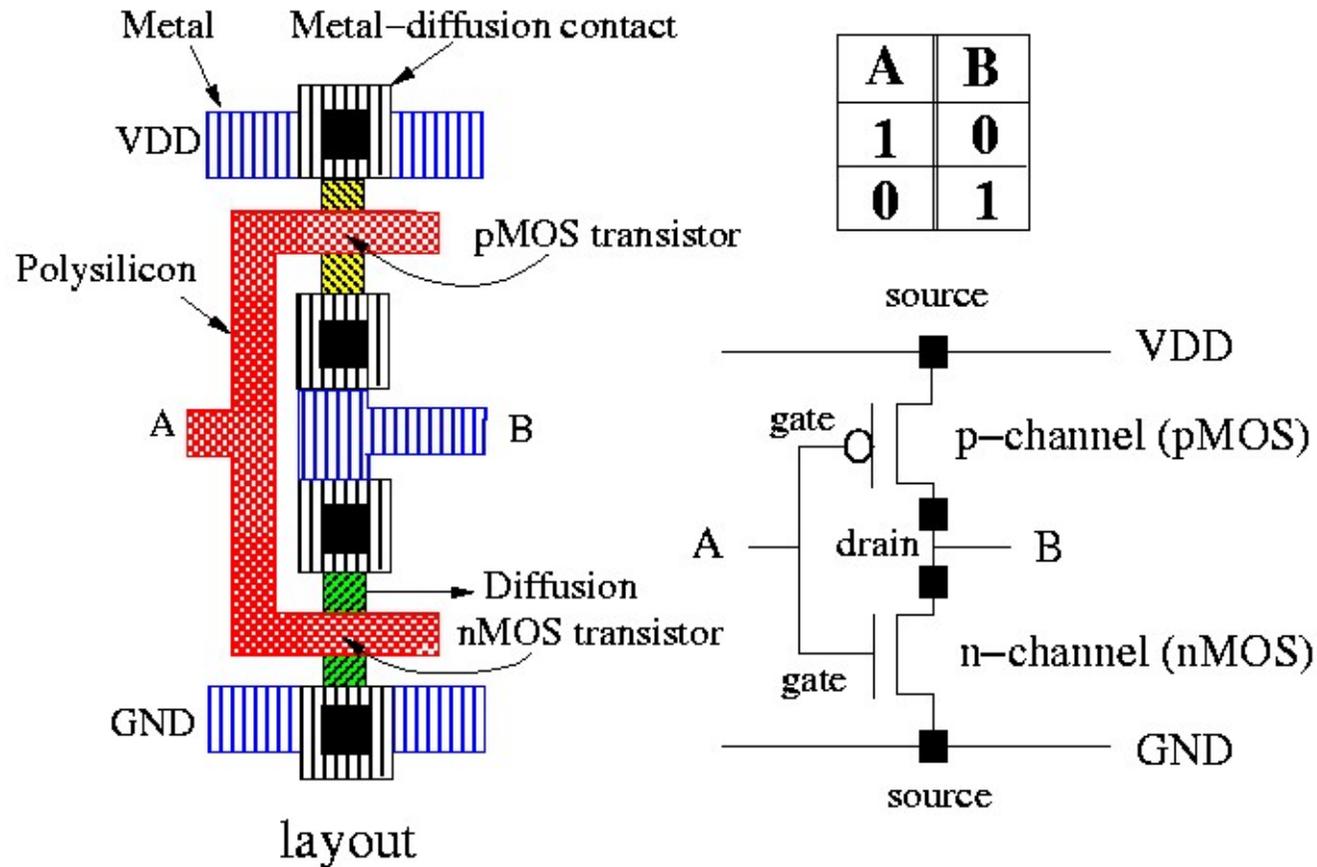
**The nMOS switch passes signal "0" well.**

# Complementary MOS (CMOS)

- The most popular VLSI technology (vs. BiCMOS, nMOS).
- CMOS uses both *n*-channel and *p*-channel transistors.
- Advantages: lower power dissipation, higher regularity, more reliable performance, higher noise margin, larger fanout, etc.
- Each type of transistor must sit in a material of the complementary type (the reverse-biased diodes prevent unwanted current flow).

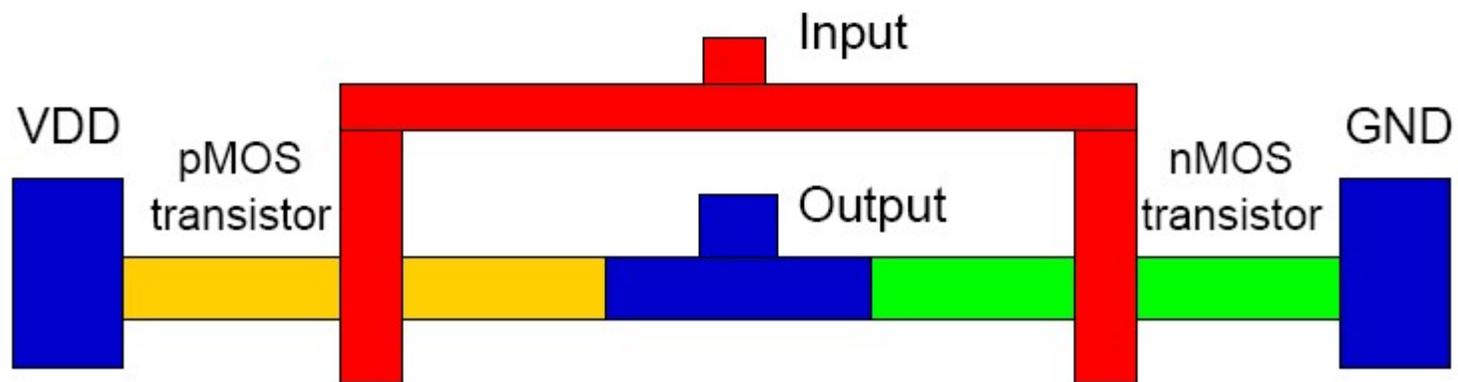
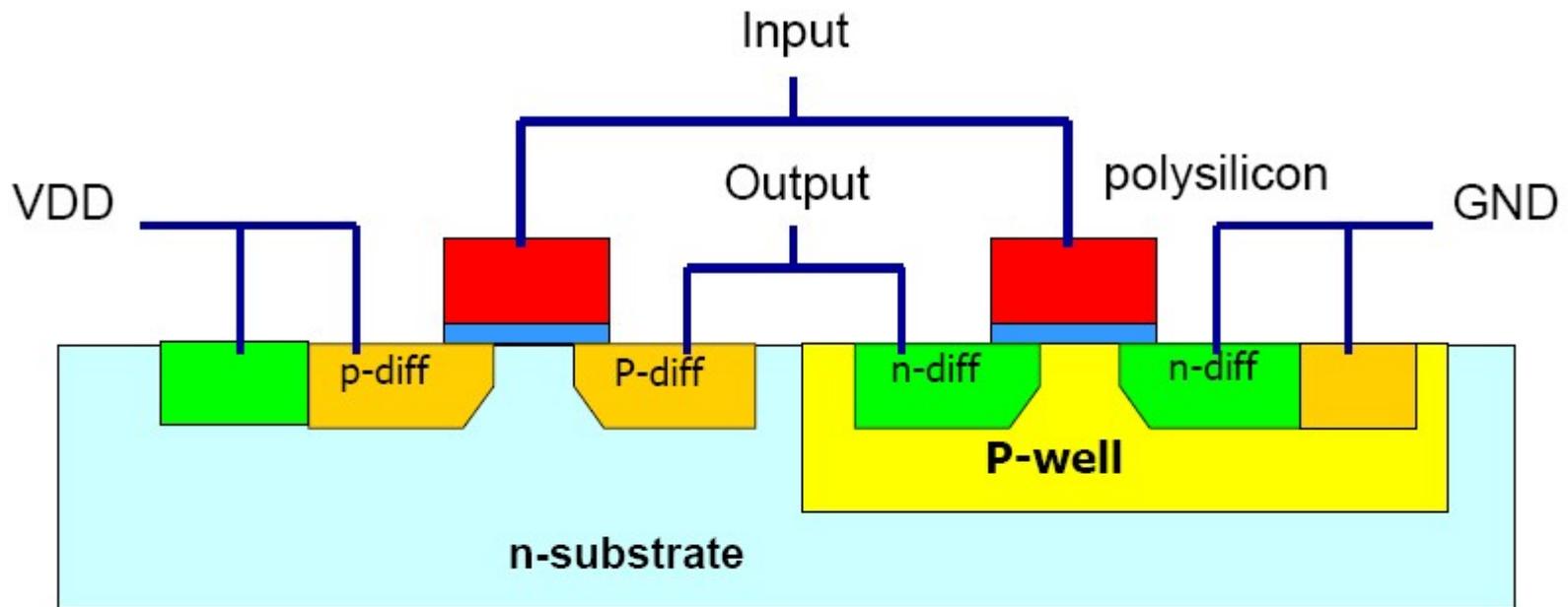


# A CMOS Inverter

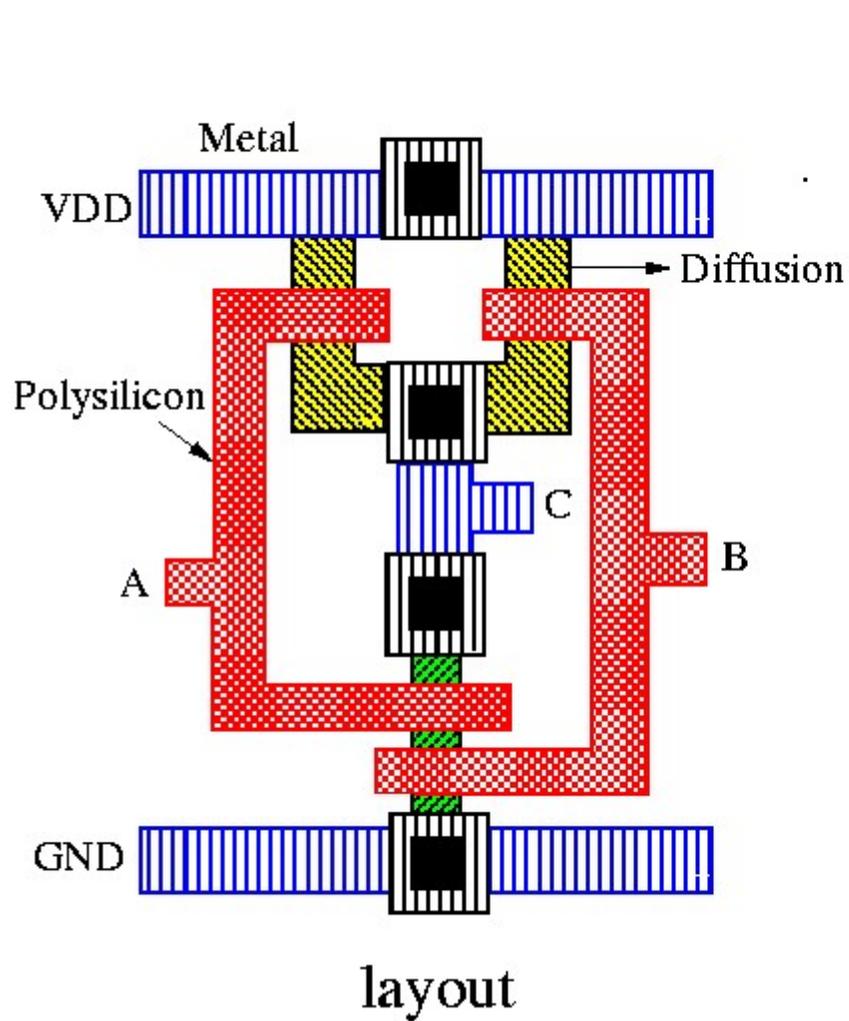


- metal 1: blue
  polysilicon: red
  p-diffusion: yellow (p-well: light yellow)
- metal 2: brown
  contact/via: black
  n-diffusion: green (n-well: light green)

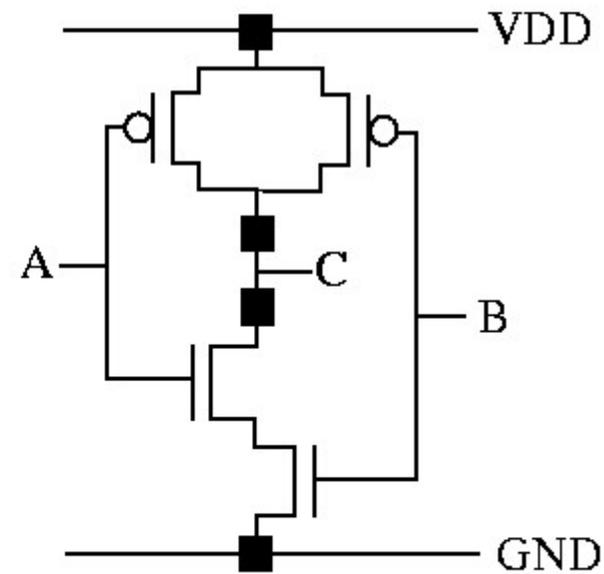
# A CMOS Inverter Structure



# A CMOS NAND Gate

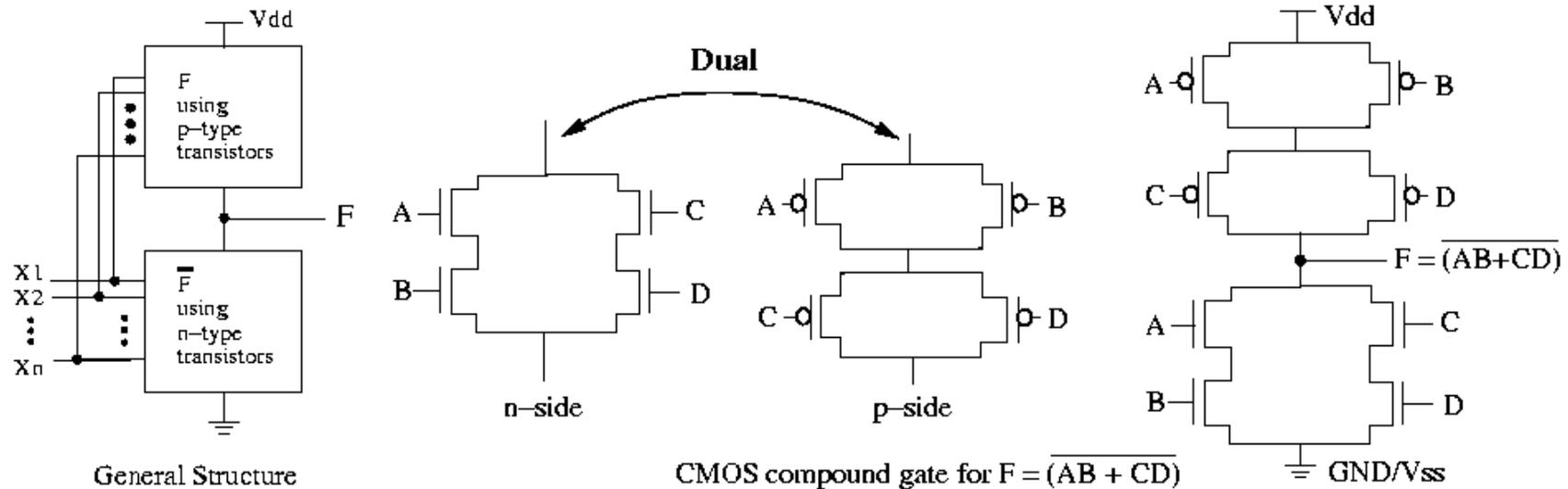


in1	in2	out
A	B	C
0	0	1
0	1	1
1	0	1
1	1	0



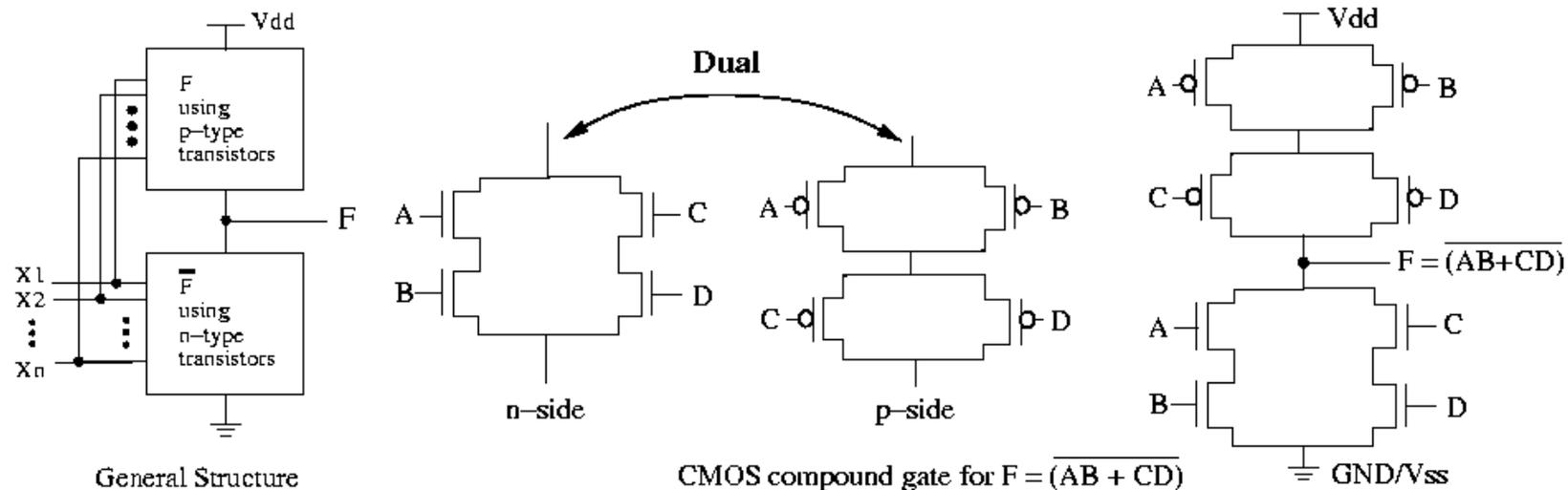
# Construction of Compound Gates

- Example:  $F = \overline{A \cdot B + C \cdot D}$ .
- Step 1 (**n**-network): **Invert**  $F$  to derive  $n$ -network ( $\overline{F} = A \cdot B + C \cdot D$ )
- Step 2 (**n**-network): Make connections of transistors:
  - AND  $\Leftrightarrow$  Series connection
  - OR  $\Leftrightarrow$  Parallel connection



# Construction of Compound Gates (cont'd)

- Step 3 (**p**-network): Expand  $F$  to derive  $p$ -network
  - $(F = \overline{AB + CD} = \overline{AB} \cdot \overline{CD} = (\overline{A} + \overline{B}) \cdot (\overline{C} + \overline{D}))$
  - **each input is inverted**
- Step 4 (**p**-network): Make connections of transistors (same as Step 2).
- Step 5: Connect the  $n$ -network to GND (typically, 0V) and the  $p$ -network to VDD (5V, 3.3V, or 2.5V, etc).



# CMOS Properties

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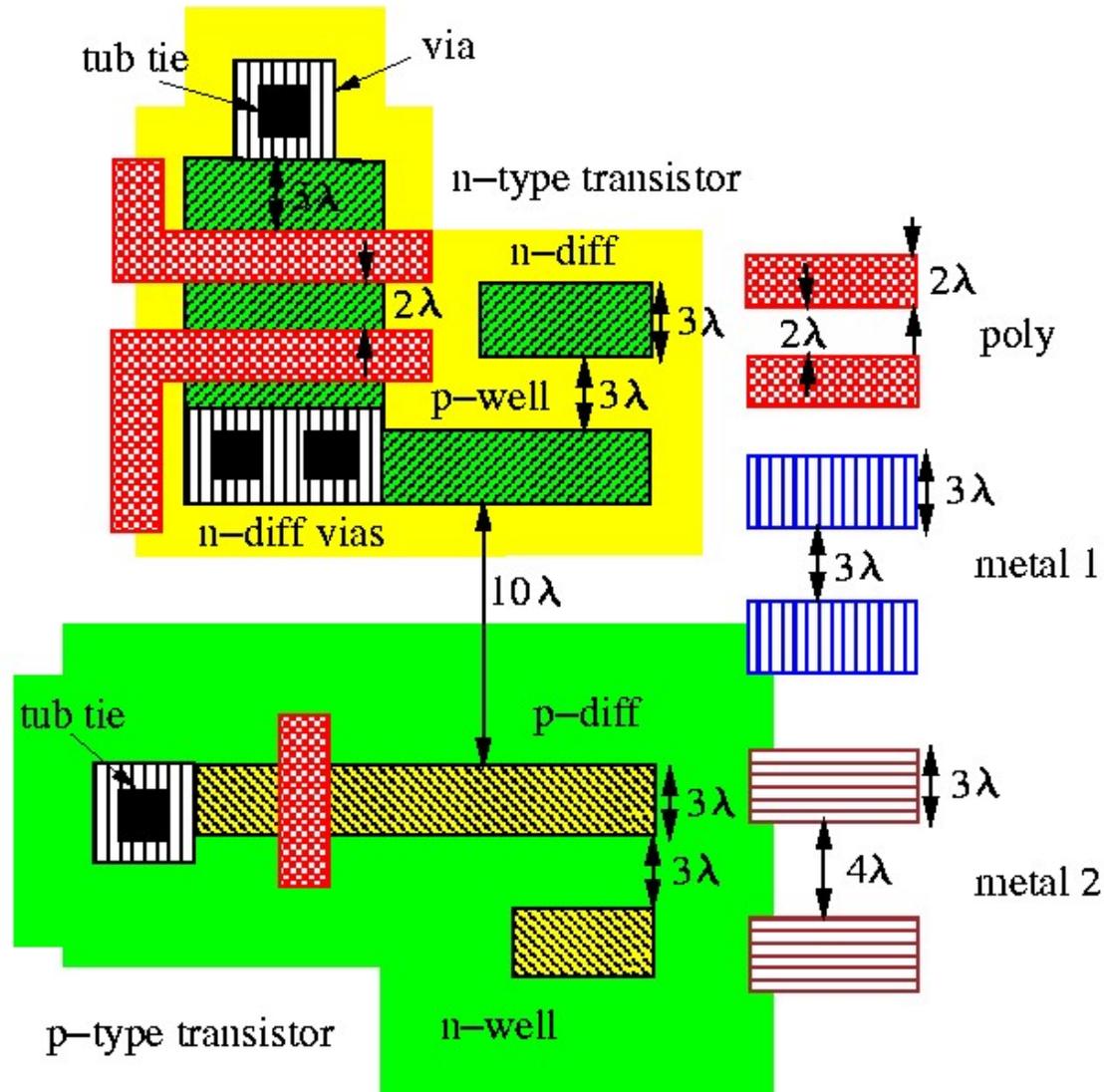
- There is always a path from one supply (VDD or GND) to the output.
- There is never a path from one supply to the other. (This is the basis for the low power dissipation in CMOS—virtually no static power dissipation.)
- There is a momentary drain of current (and thus power consumption) when the gate switches from one state to another.
  - Thus, CMOS circuits have dynamic power dissipation.
  - The amount of power depends on the switching frequency.

# Design Rules

---

- Layout rules are used for preparing the masks for fabrication.
- Fabrication processes have inherent limitations in accuracy.
- Design rules specify geometry of masks to optimize yield and reliability (trade-offs: area, yield, reliability).
- Three major rules:
  - **Wire width:** Minimum dimension associated with a given feature.
  - **Wire separation:** Allowable separation.
  - **Contact:** overlap rules.
- Two major approaches:
  - **“Micron” rules:** stated at micron resolution.
  - **$\lambda$  rules:** simplified micron rules with limited **scaling** attributes.
- $\lambda$  may be viewed as the size of minimum feature.
- Design rules represents a tolerance which insures very high probability of correct fabrication (not a hard boundary between correct and incorrect fabrication).
- Design rules are determined by experience.

# Example: SCMOS Design Rules



# MOSIS Layout Design Rules

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- MOSIS design rules (SCMOS rules) are available at <http://www.mosis.org>.
- 3 basic design rules: Wire width, wire separation, contact rule.
- MOSIS design rule examples

R1	Min active area width	3 $\lambda$
R3	Min poly width	2 $\lambda$
R4	Min poly spacing	2 $\lambda$
R5	Min gate extension of poly over active	2 $\lambda$
R8	Min metal width	3 $\lambda$
R9	Min metal spacing	3 $\lambda$
R10	Poly contact size	2 $\lambda$
R11	Min poly contact spacing	2 $\lambda$